

High sensitivity gas-density profilometry for laser- and beam-driven plasma acceleration experiments

Status report

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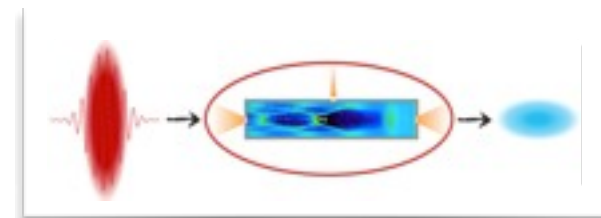


N. Delbos, L. Goldberg, T. Kleinwächter, A. Maier, J. Osterhoff,
C. A. J. Palmer, M. Schnepf, J.-P. Schwinkendorf

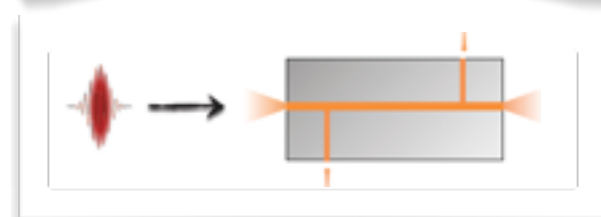
In collaboration with S. Hooker and his group

Part of the **LAOLA** collaboration

Outline



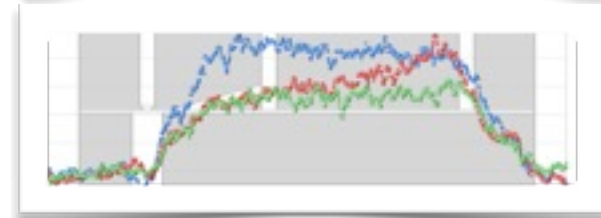
> Motivation



> Controlled injection mechanisms



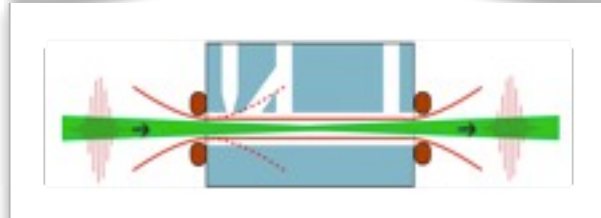
> Target simulation and fabrication



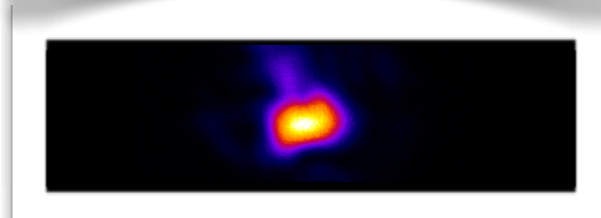
> Longitudinal gas density profile and absolute calibration



> Transverse density shaping and single shot guiding



> Discharge seeding



> Summary and conclusion

Plasma acceleration: Stability and reproducibility

Electron beam fluctuations may originate from

variations in

laser pulse parameters

→ spatial and temporal energy profiles, pointing

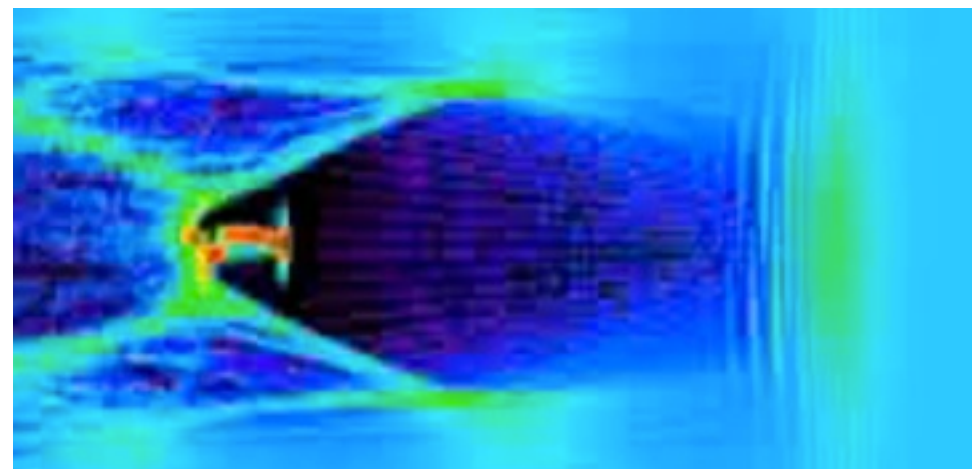
variations in

target conditions

→ spatial and temporal 3D density profile

*amplified through
nonlinear processes*

→ e.g. wavebreaking, ...



Improve control over and stabilize
crucial laser parameters

e.g. Popp *et al.*, Phys. Rev. Lett. 105, 215001 (2010)
Gonsalves *et al.*, Phys. Plasmas 17, 056706 (2010)

Develop stable, tailored
plasma sources

e.g. Osterhoff *et al.*, Phys. Rev. Lett. 101, 085002 (2008)

energy spread

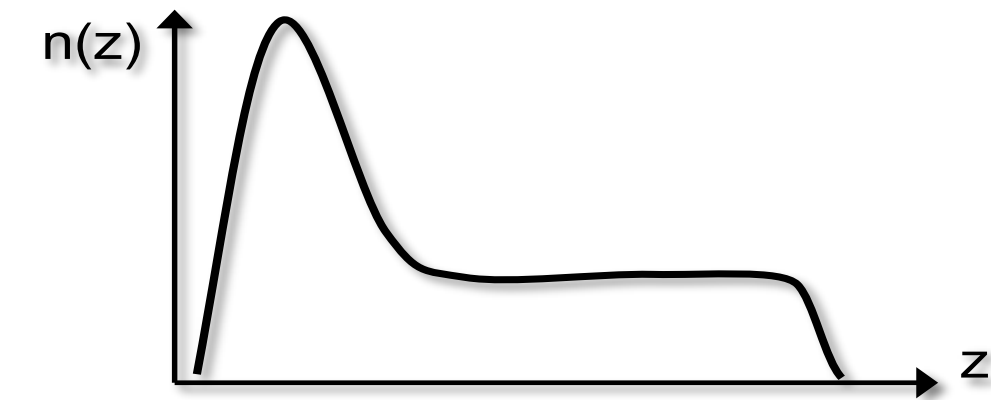
Control of phase-space
population by controlled
injection

dephasing

longitudinal profile taper

Controlled injection: Various mechanisms to be compared

- > Density down ramp injection



Controlled injection: Various mechanisms to be compared

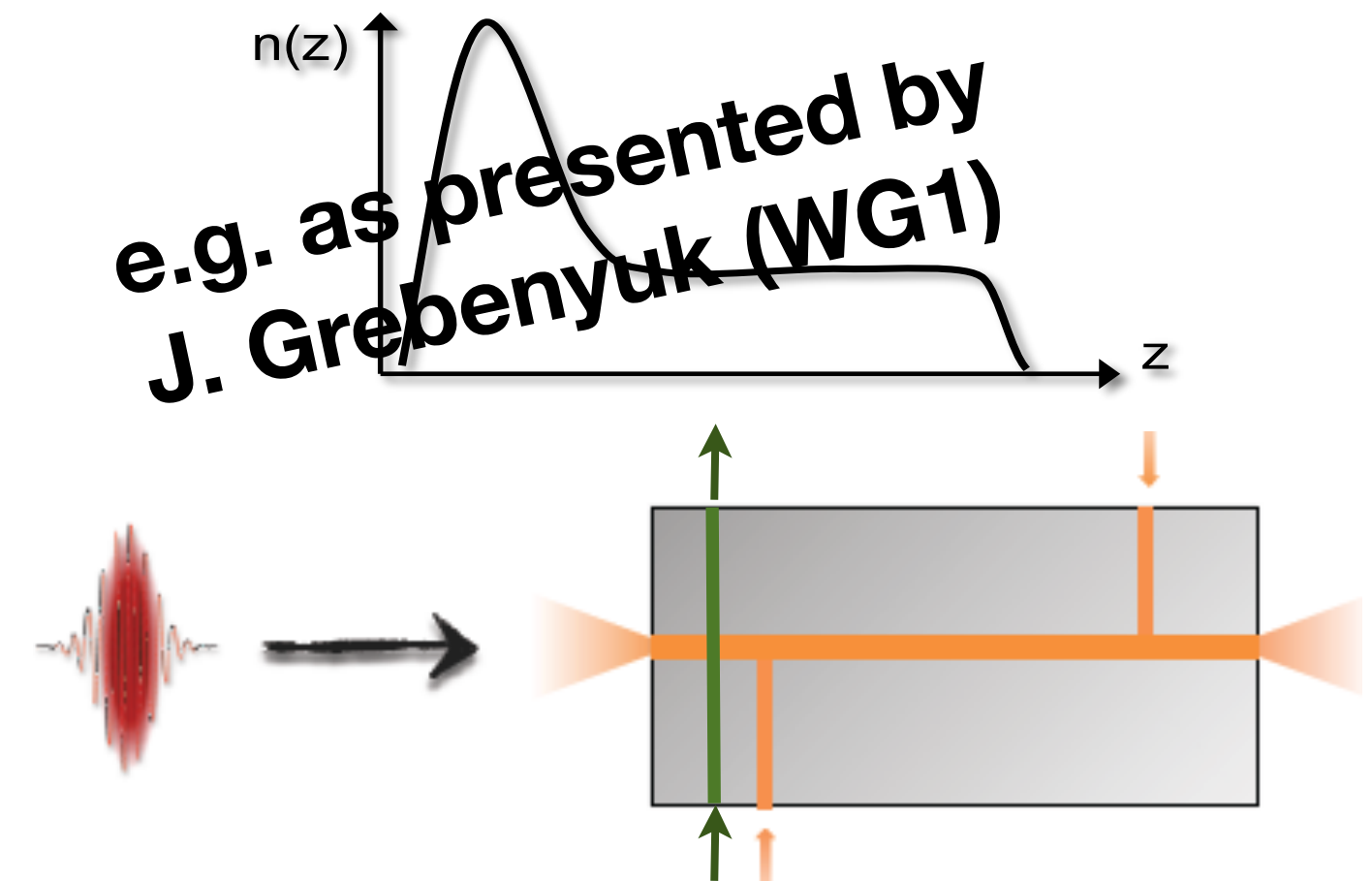
- > Density down ramp injection



Controlled injection: Various mechanisms to be compared

> Density down ramp injection

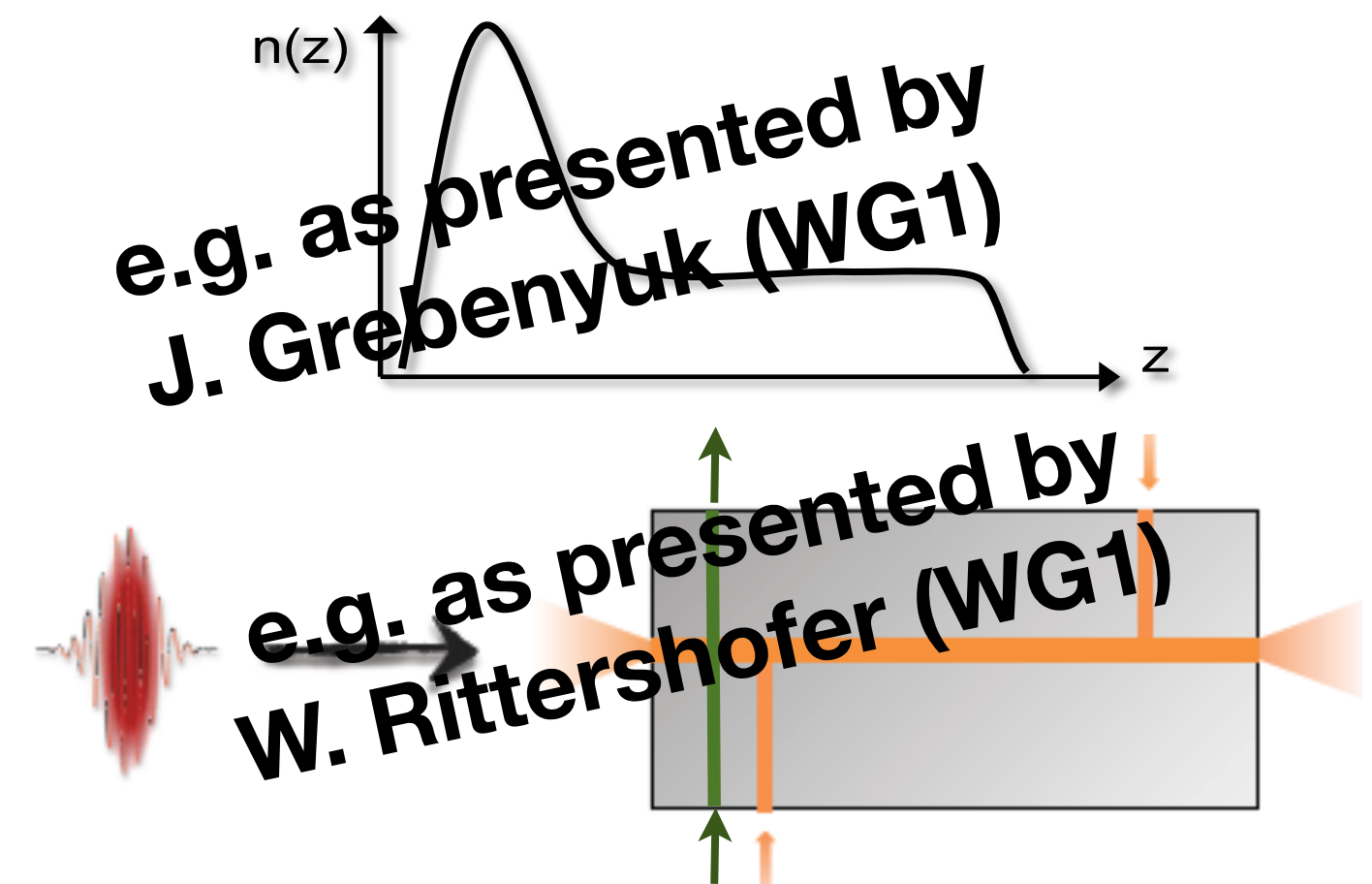
> Ionisation injection



Controlled injection: Various mechanisms to be compared

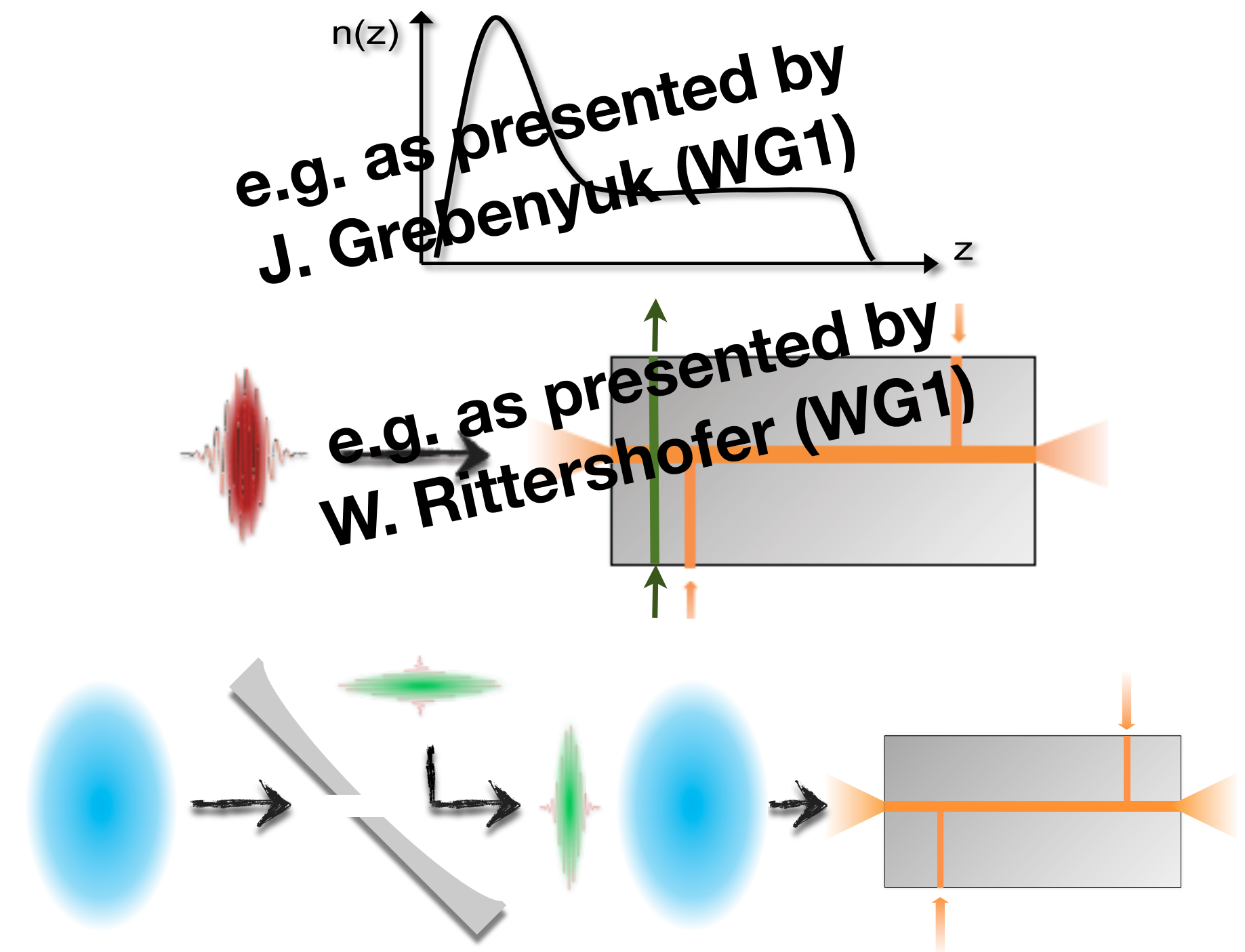
> Density down ramp injection

> Ionisation injection



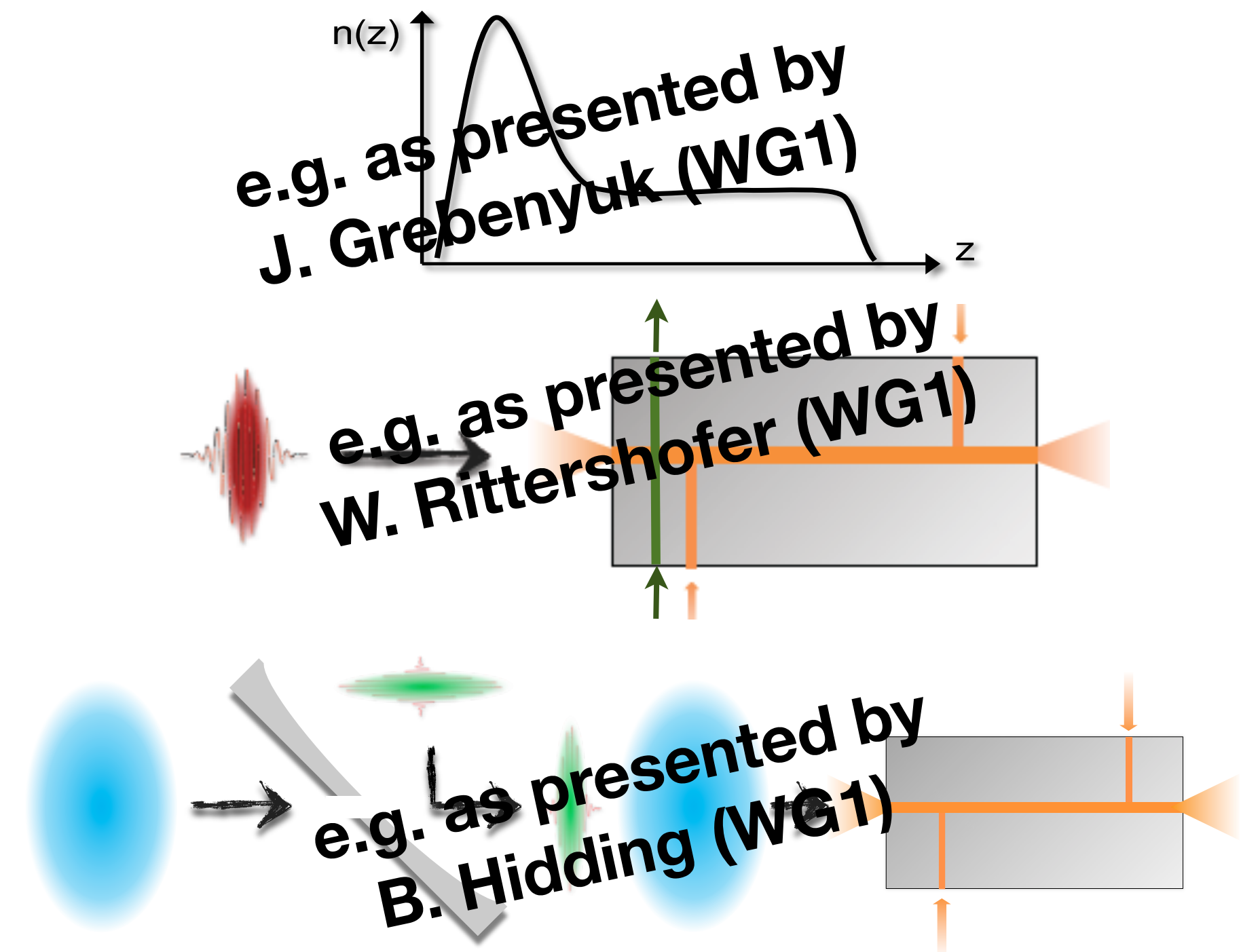
Controlled injection: Various mechanisms to be compared

- > Density down ramp injection
- > Ionisation injection
- > mediated ionisation injection



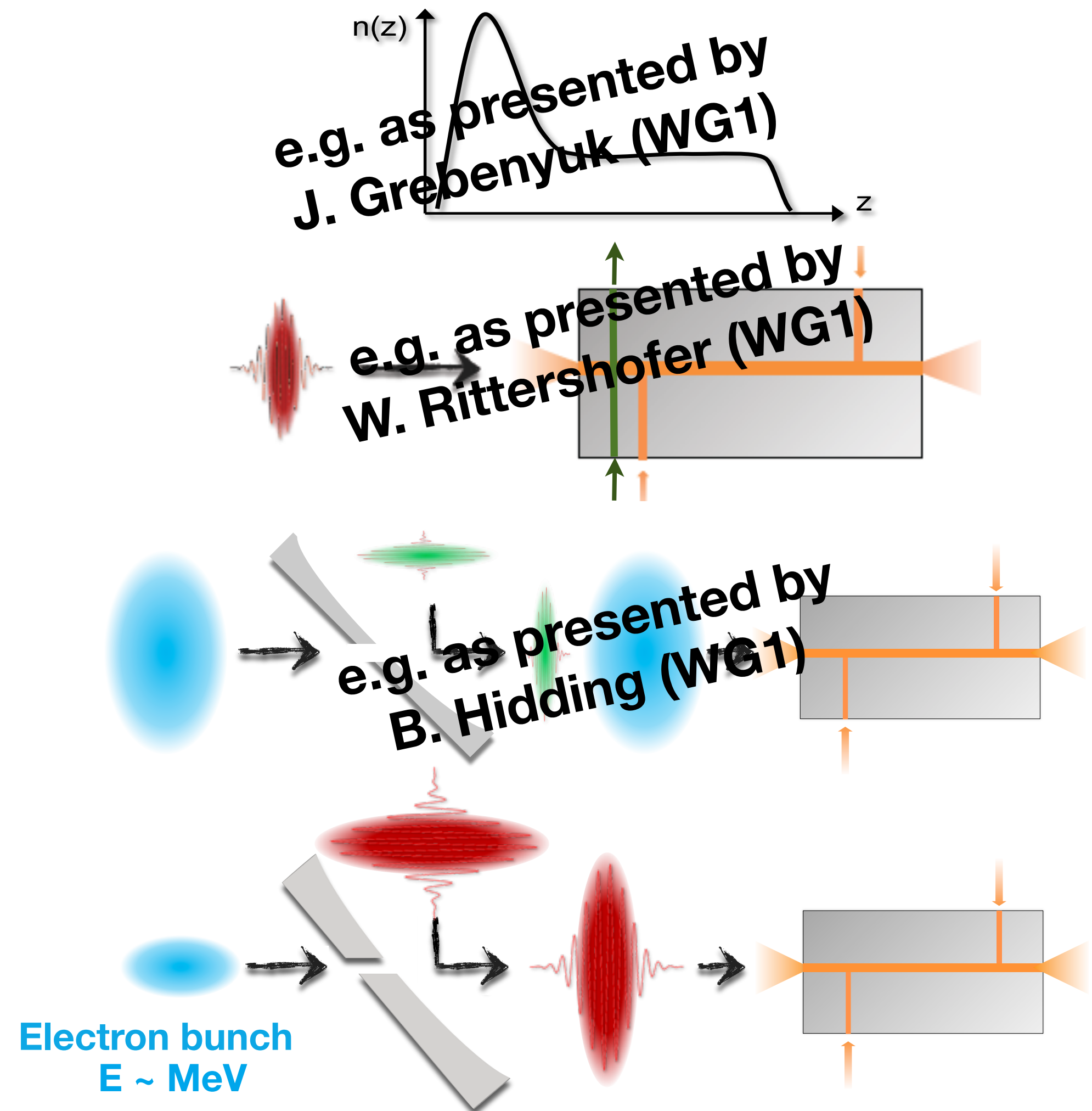
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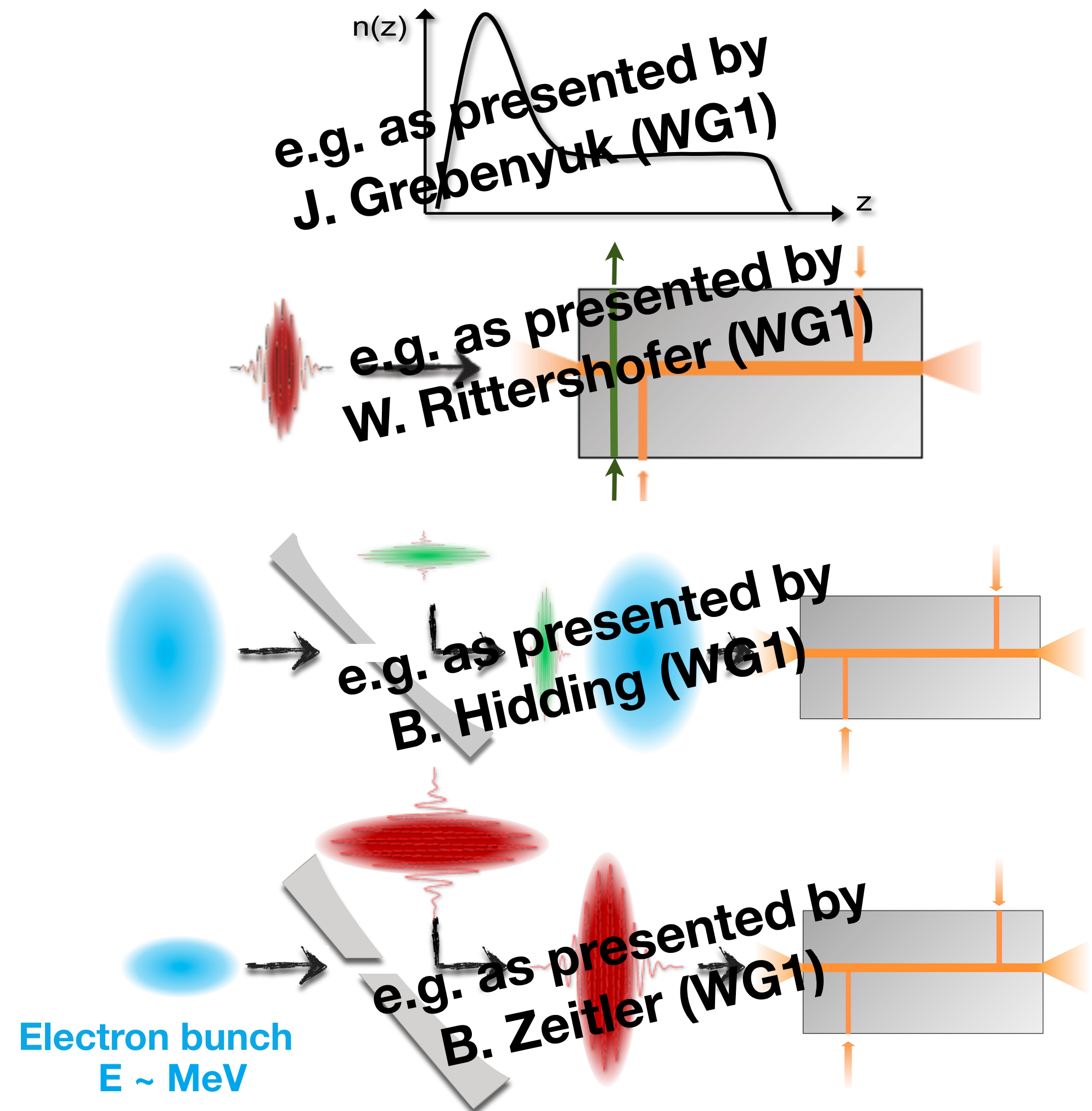
Controlled injection: Various mechanisms to be compared

- > Density down ramp injection
- > Ionisation injection
- > mediated ionisation injection
- > External injection



Controlled injection: Various mechanisms to be compared

- > Density down ramp injection
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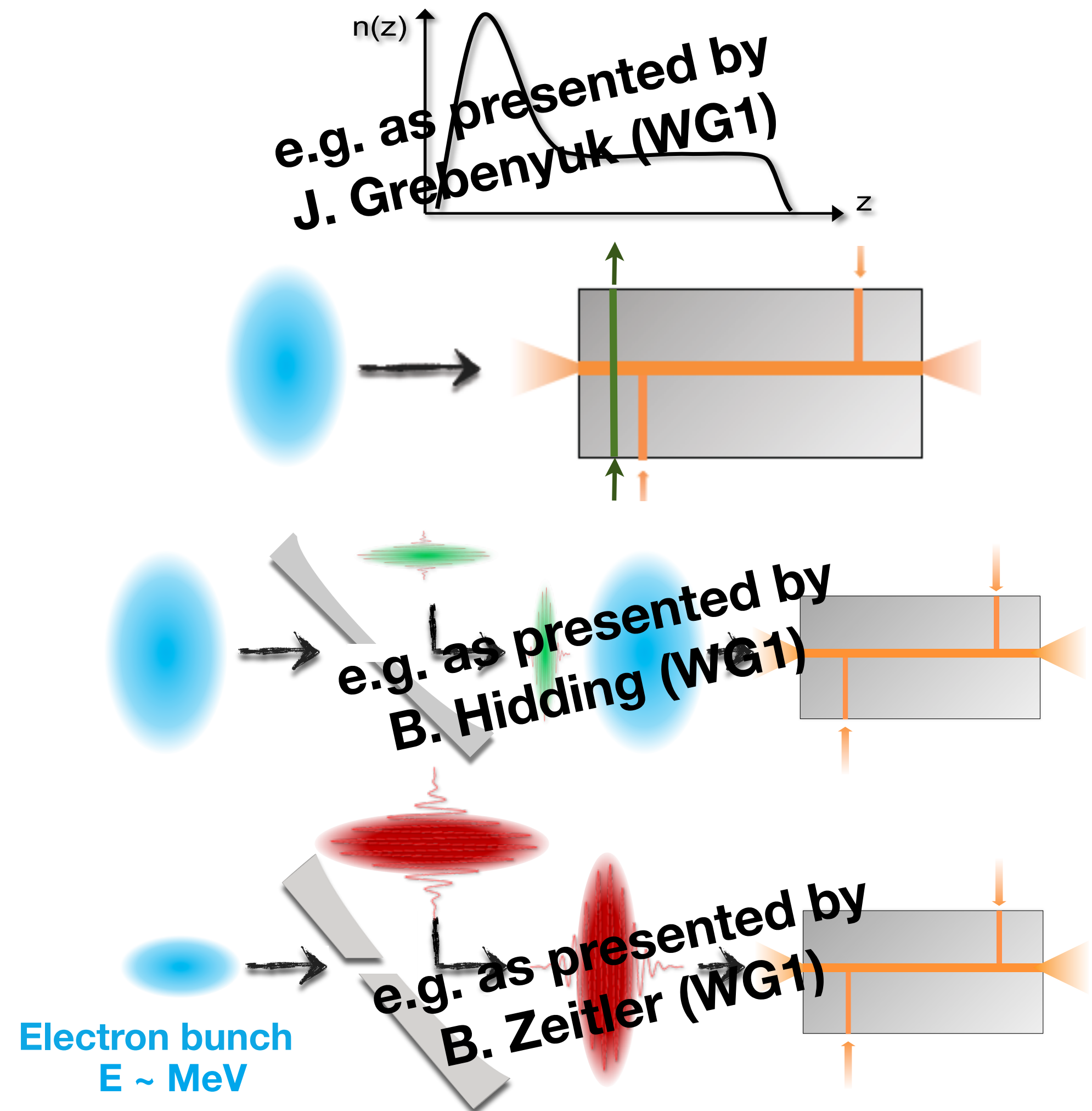
Controlled injection: Various mechanisms to be compared

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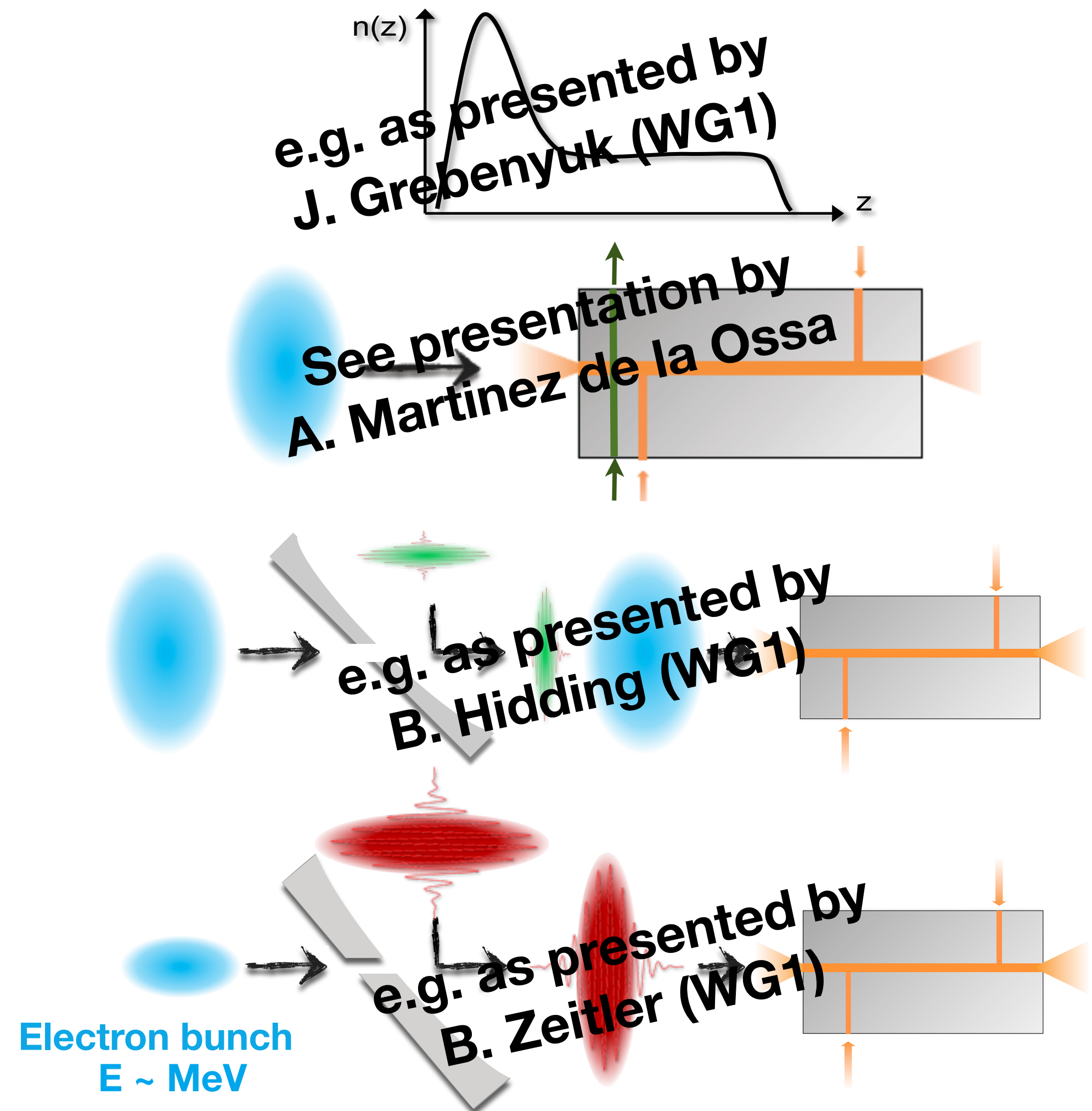
> mediated ionisation injection

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Controlled injection: Various mechanisms to be compared

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- > Ionisation injection
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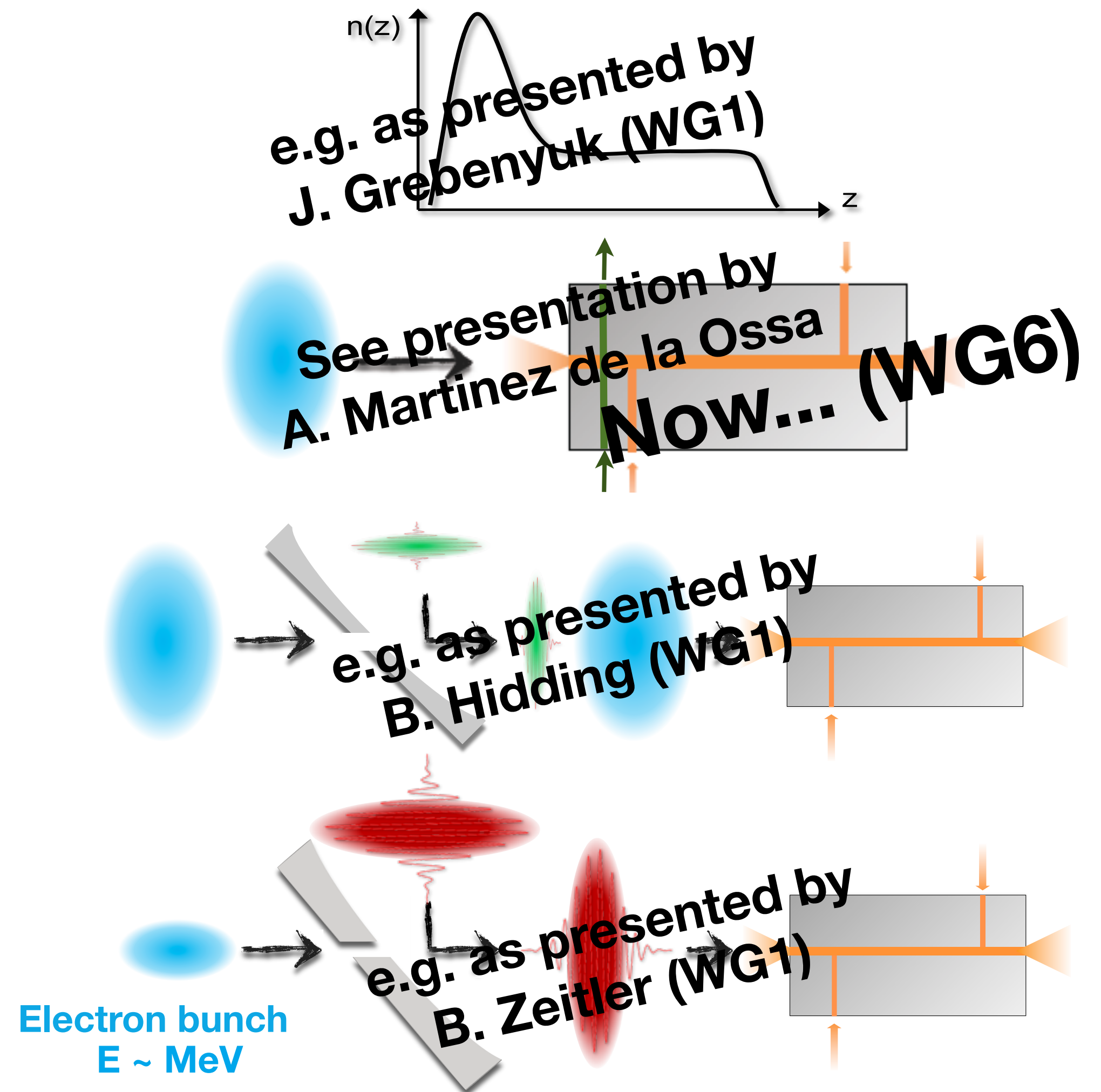
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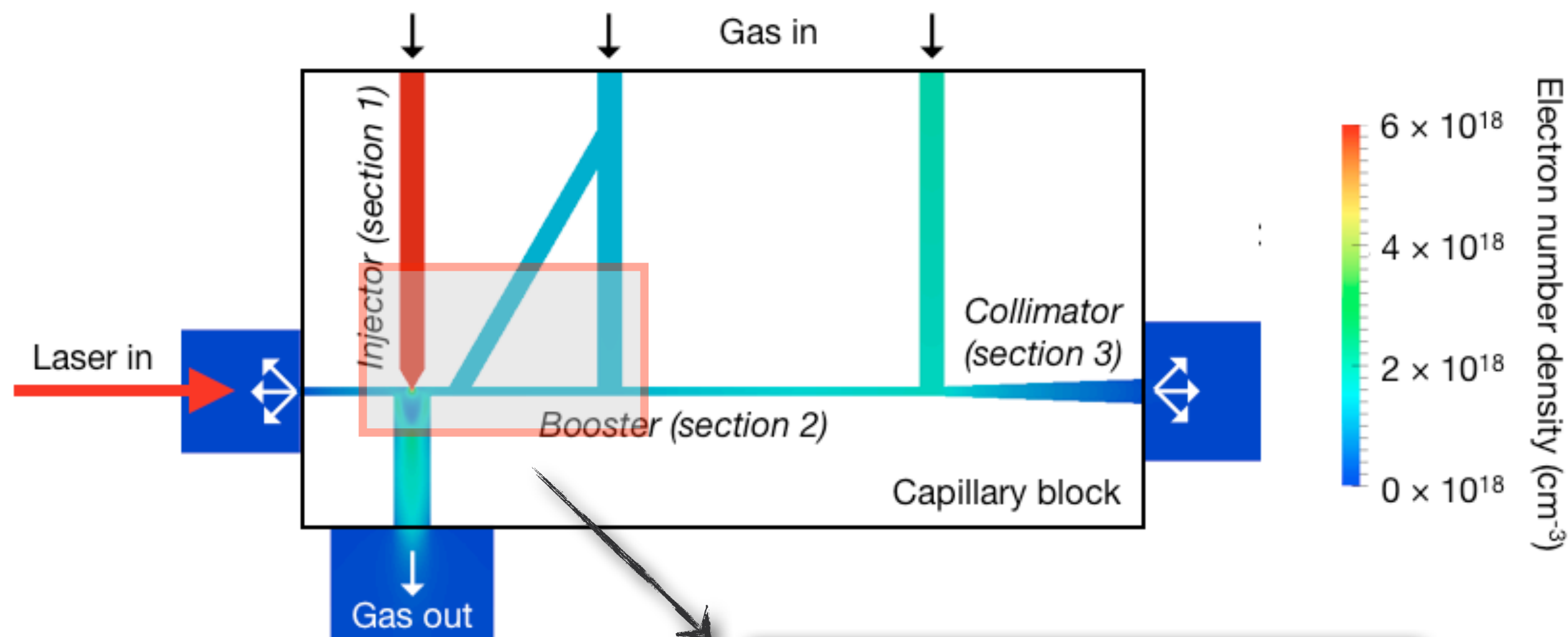
> mediated ionisation injection

> External injection

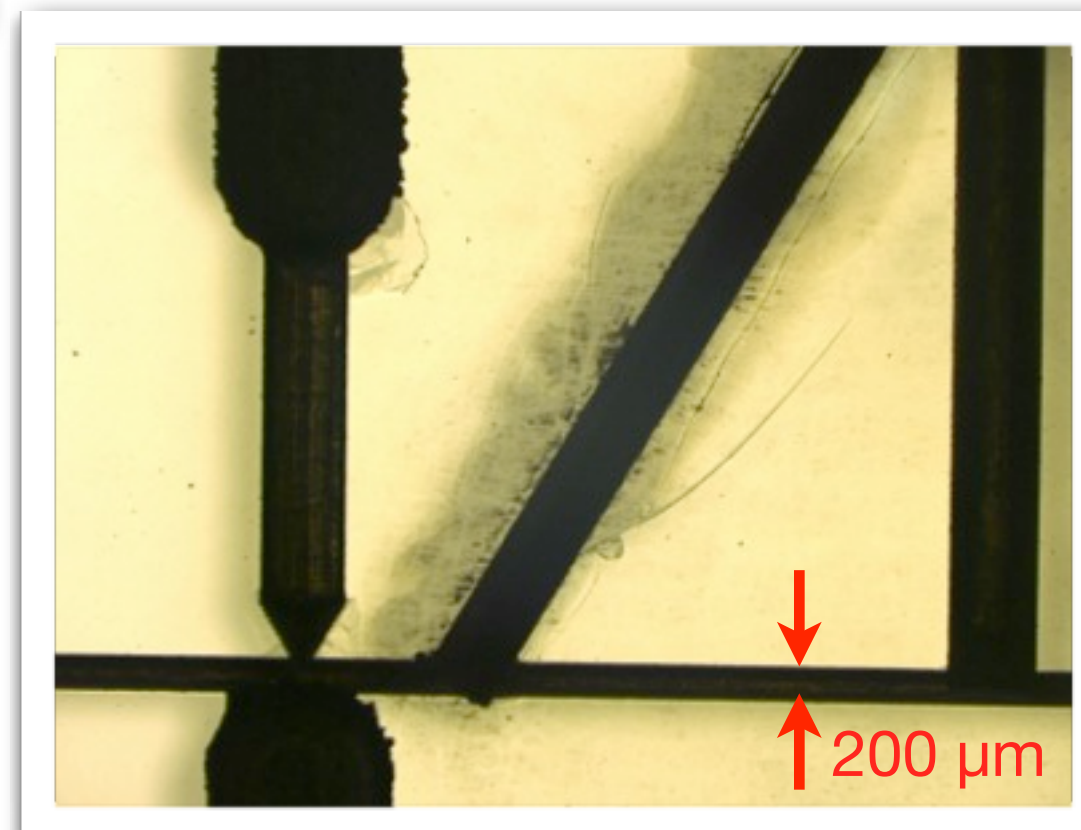


The goal: development of tailored plasma sources for controlled electron injection, acceleration and emission

Example: Segmented capillary discharge waveguide (injector, booster, collimator)

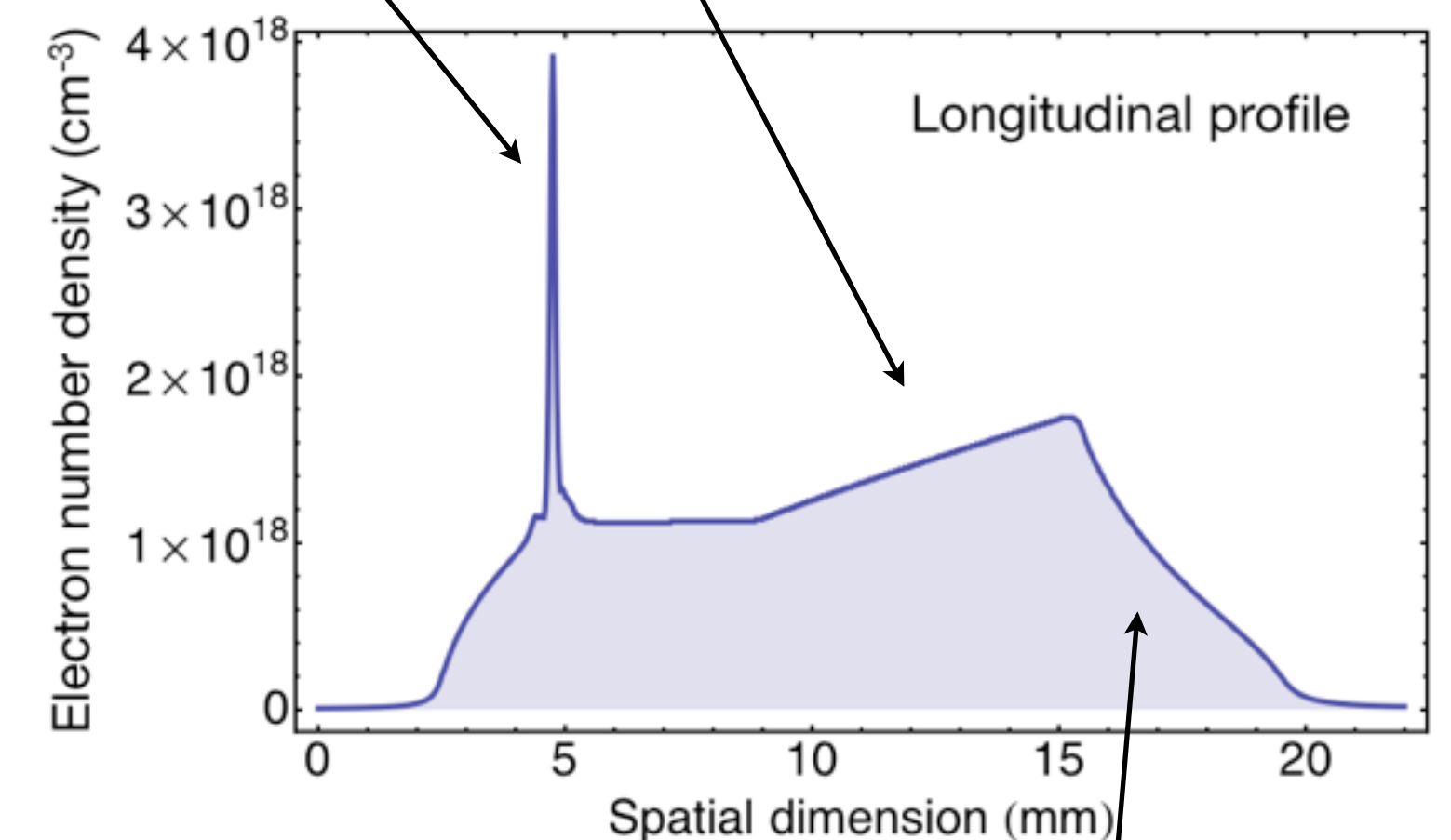


Femtosecond-laser machining
into sapphire



C. G. R. Geddes, *PRL* **100**, 215004 (2008)

W. Rittershofer, *Phys. Plasmas* **17**, 063104 (2010)

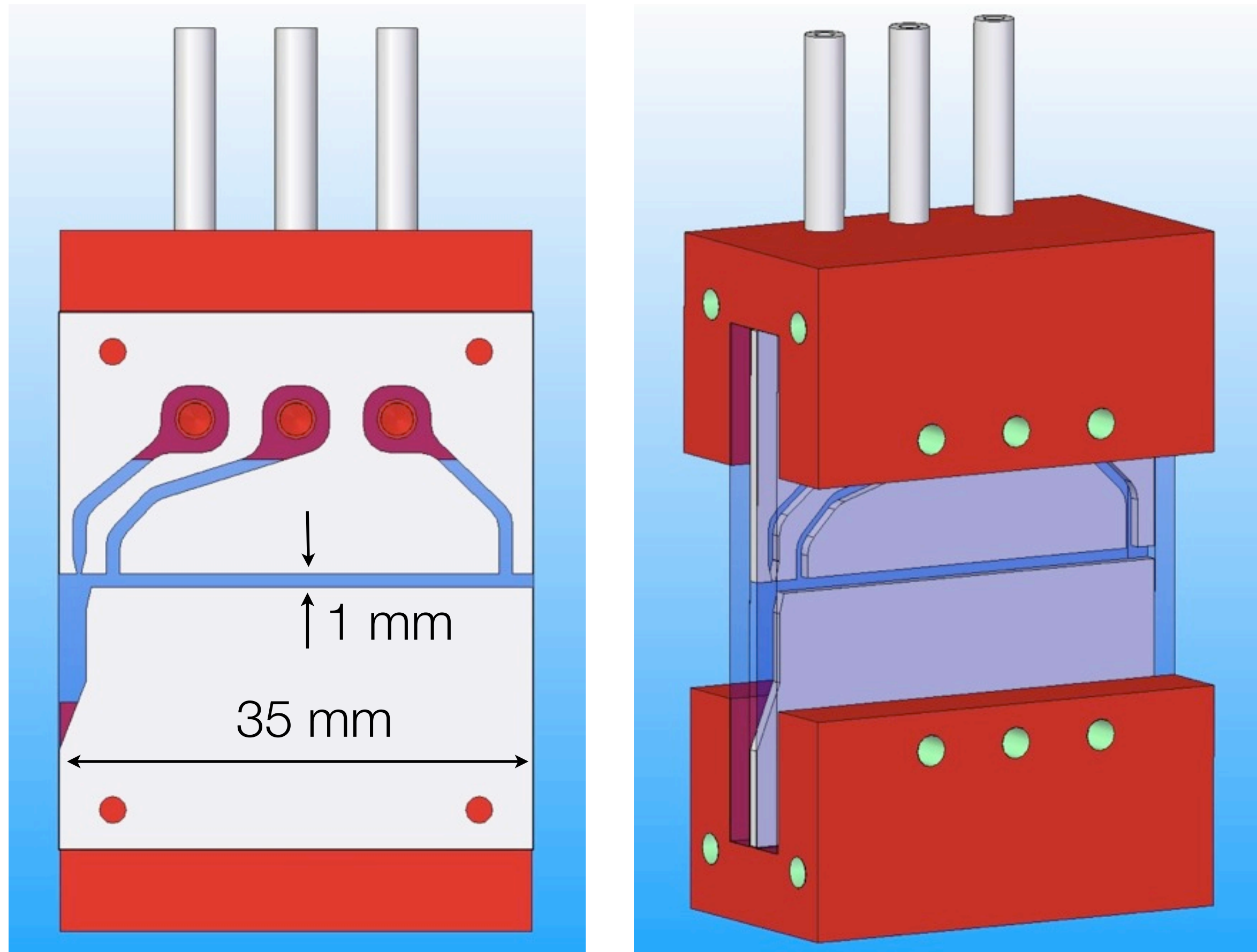


T. Mehrling, *Master Thesis*
C.M.S. Sears et al, *Phys. Rev. ST
Accel. Beams* **11**, (2008) 101301

Full 3D simulations with fluid code **OpenFOAM**

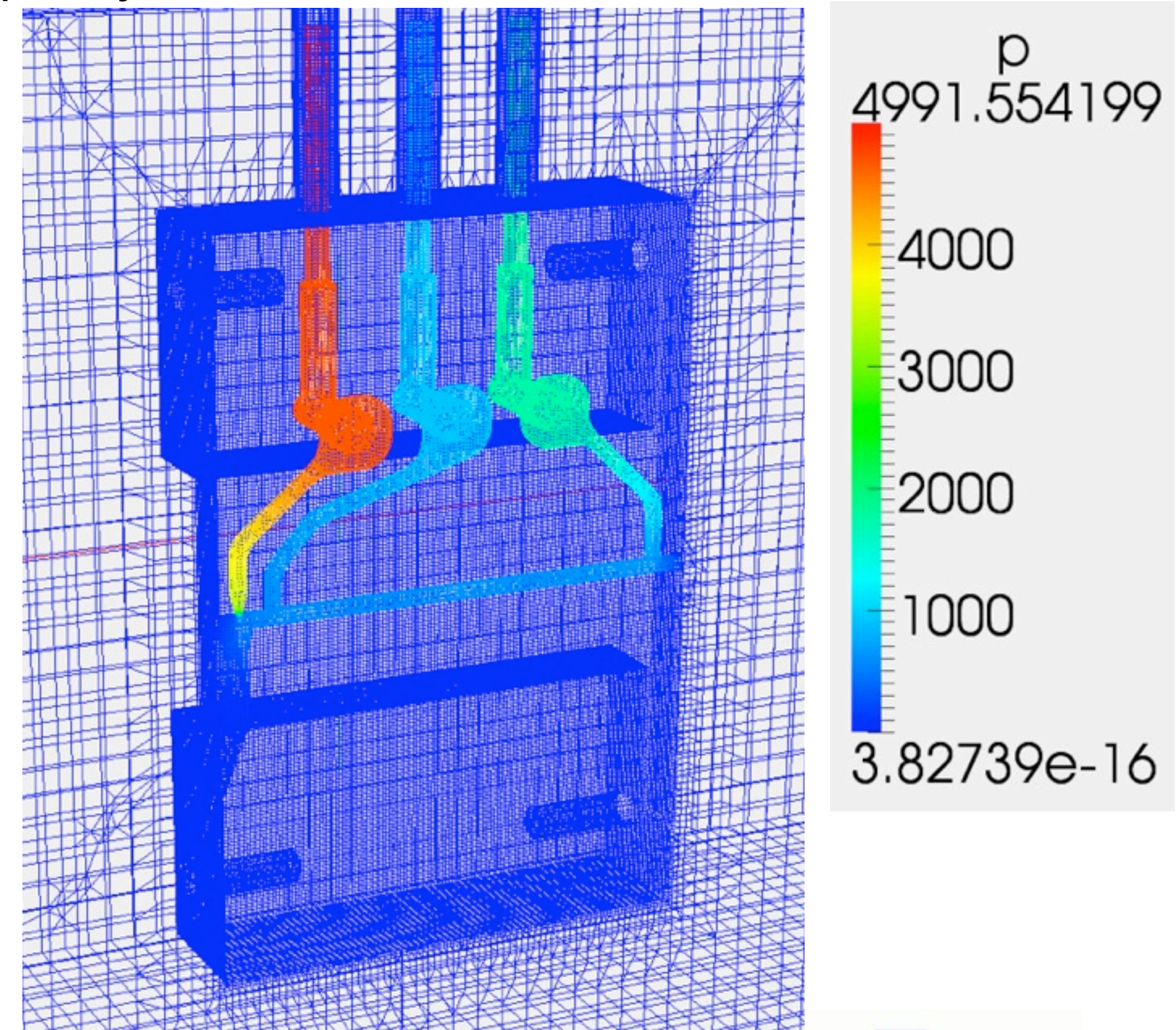
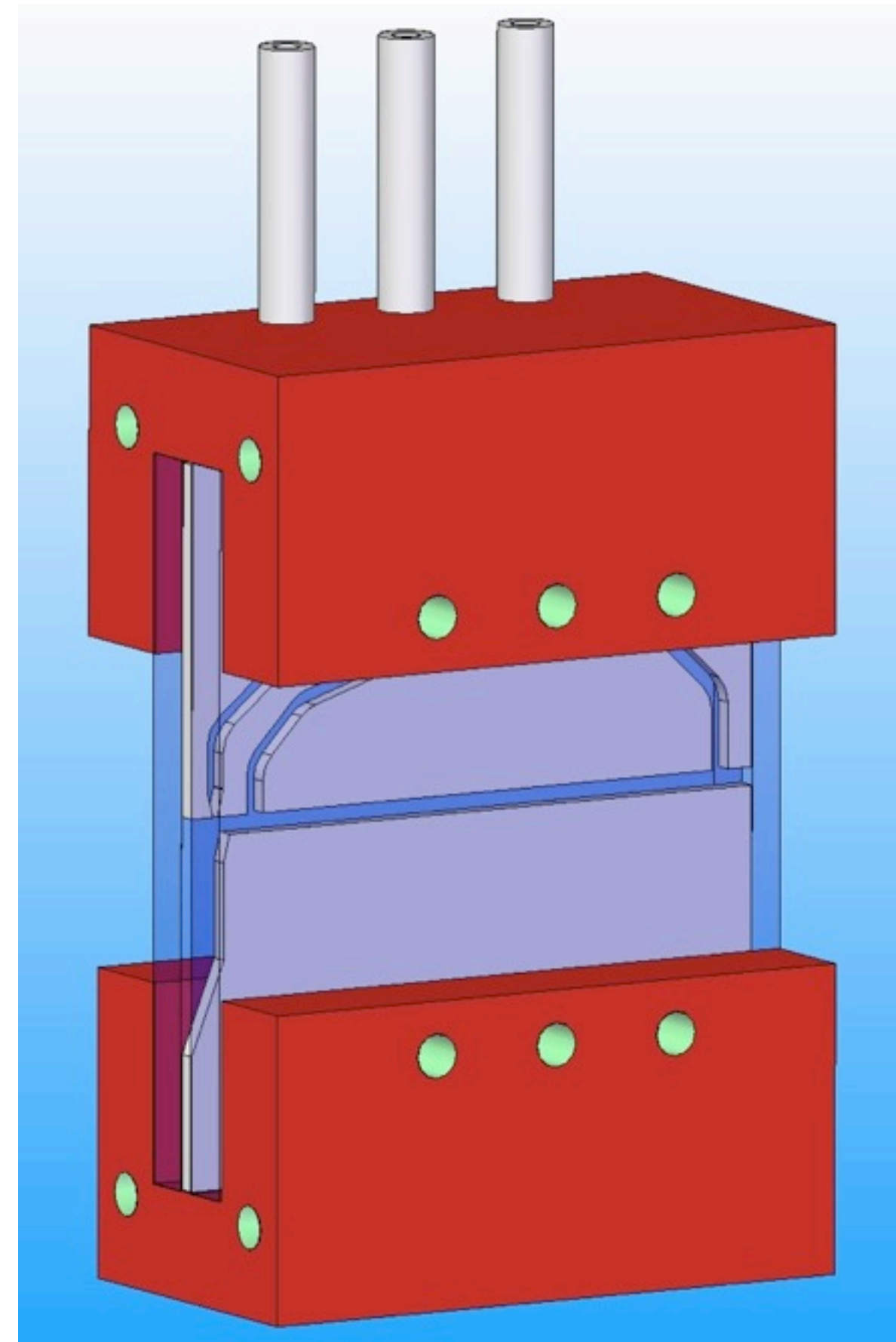
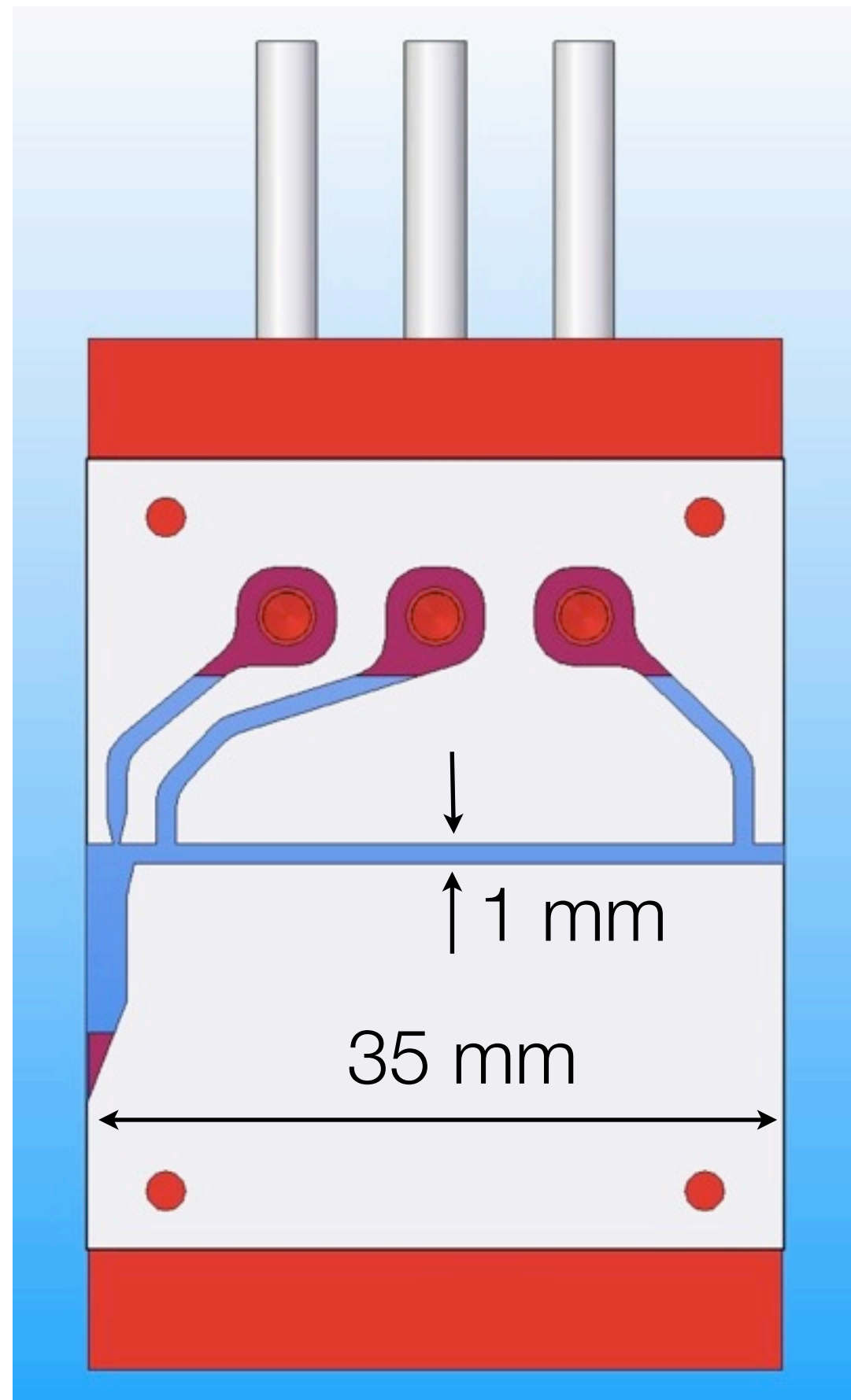
The goal: development of tailored plasma sources for controlled electron injection, acceleration and emission II

Example: Density tapered gas cell, features similar to capillary



The goal: development of tailored plasma sources for controlled electron injection, acceleration and emission II

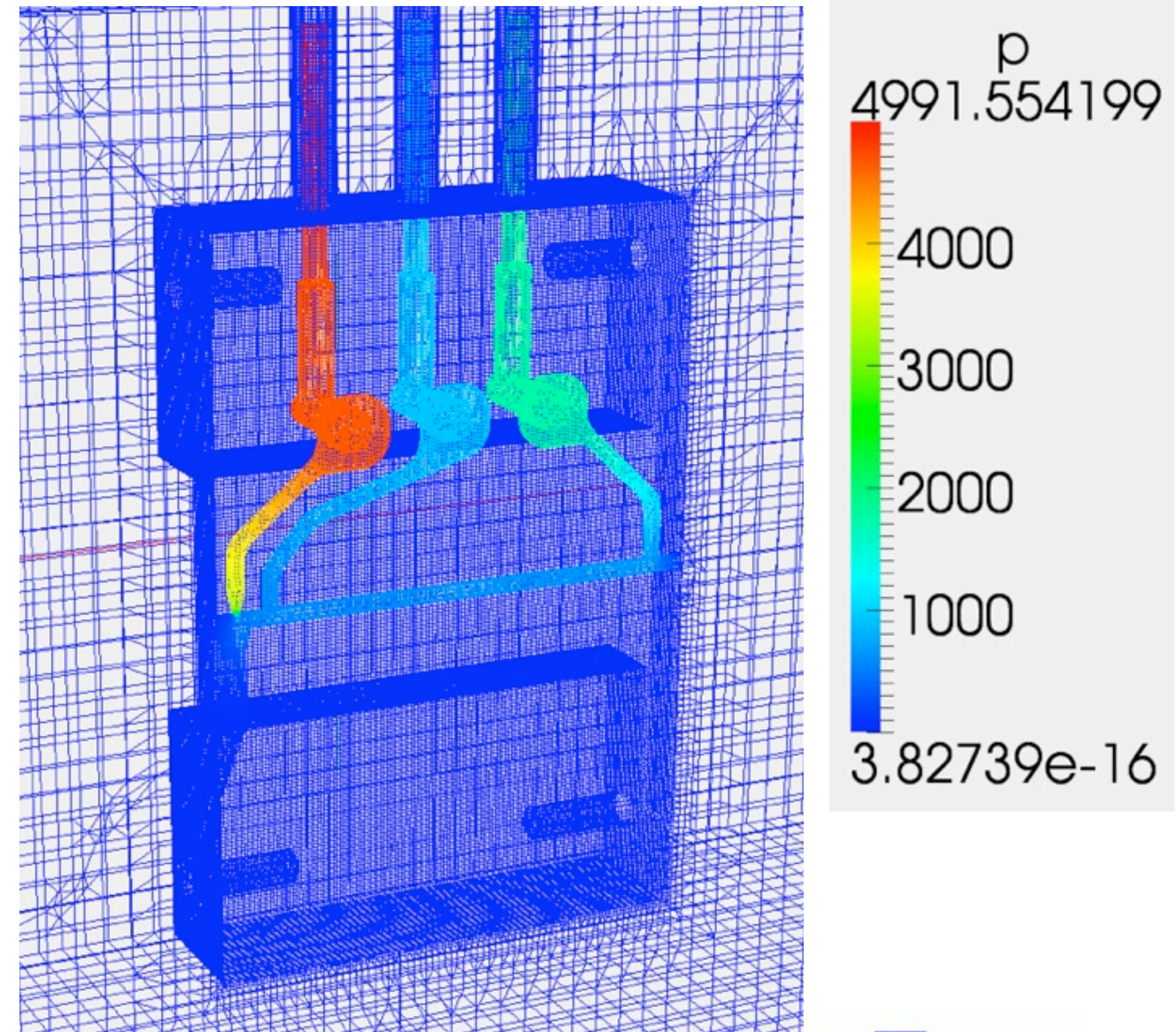
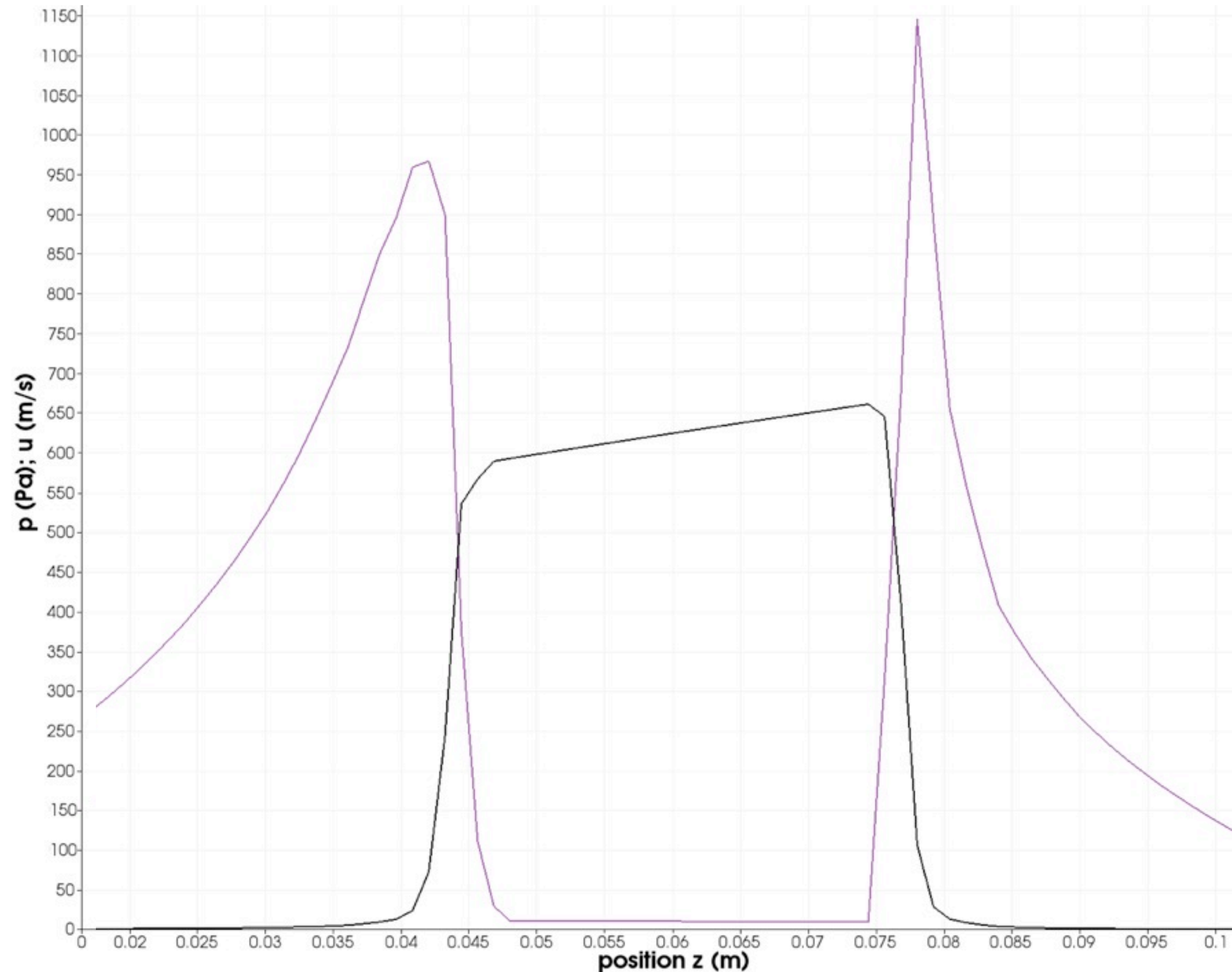
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Full 3D simulations with fluid code OpenFOAM

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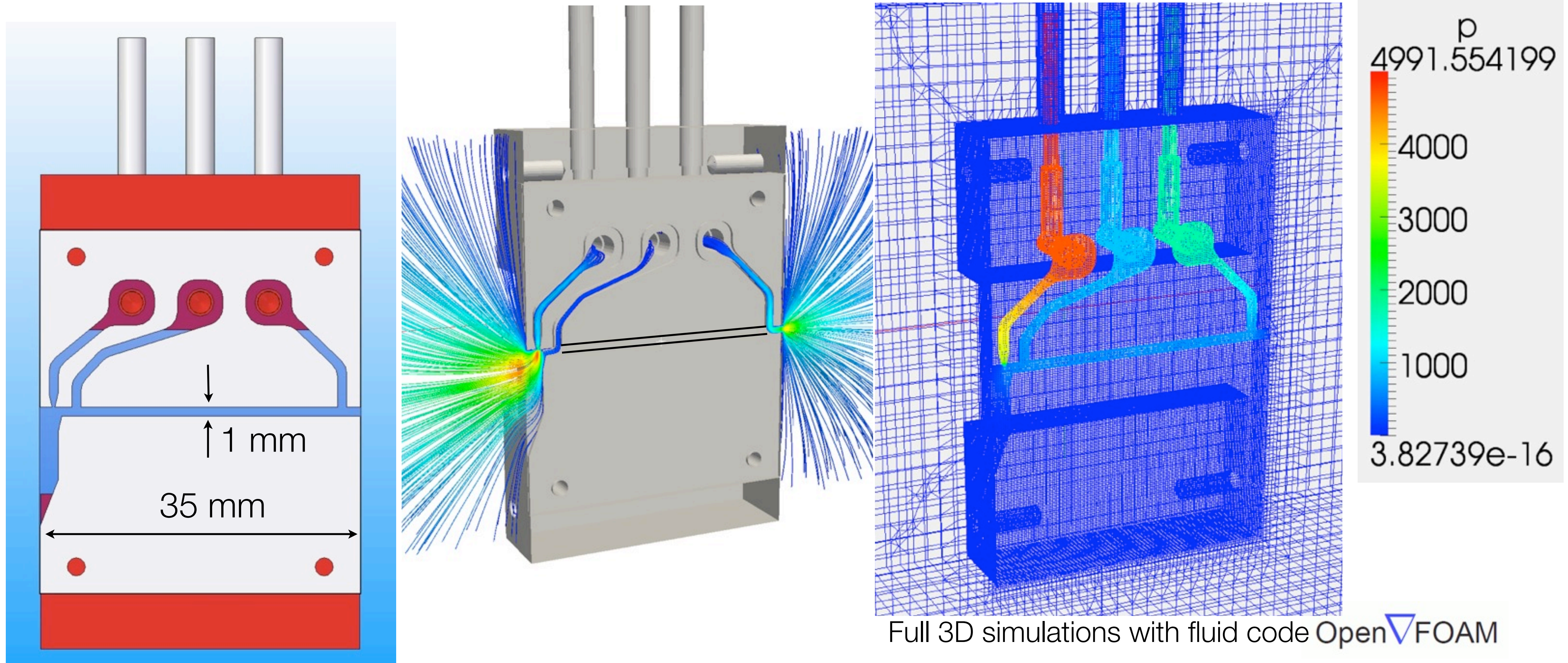
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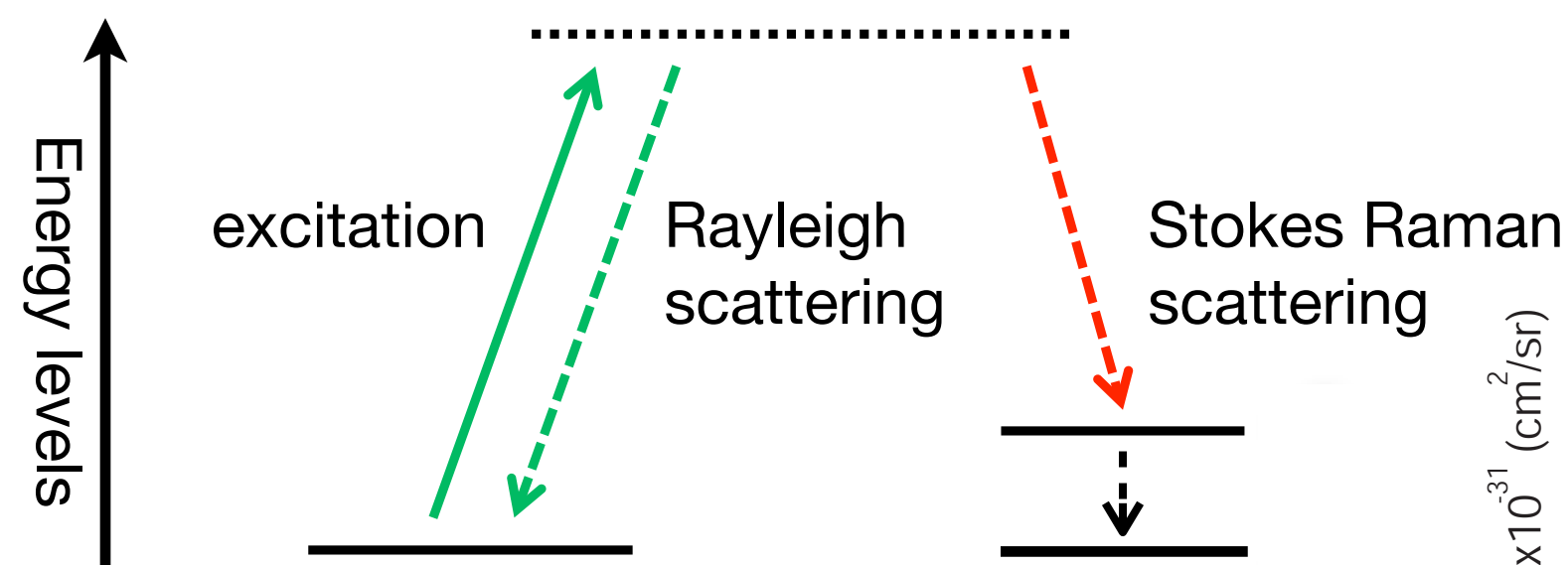


Raman scattering diagnostics: Setup

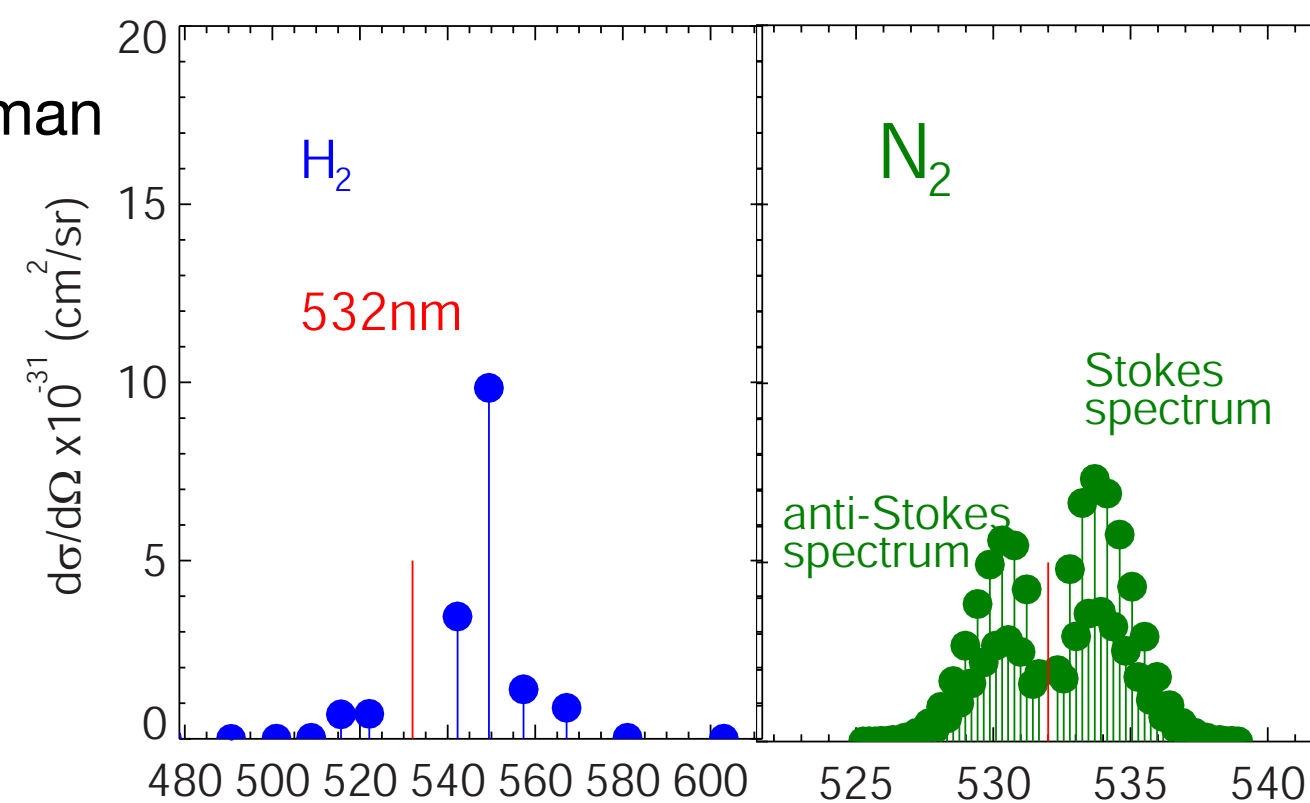
Technique: Raman scattering for longitudinal profile

- scattered intensity proportional to gas density: $I_{\text{Raman}} = n_{\text{Gas}} \cdot \sigma \cdot I_{\text{Laser}}$
- non resonant technique → filters can be used

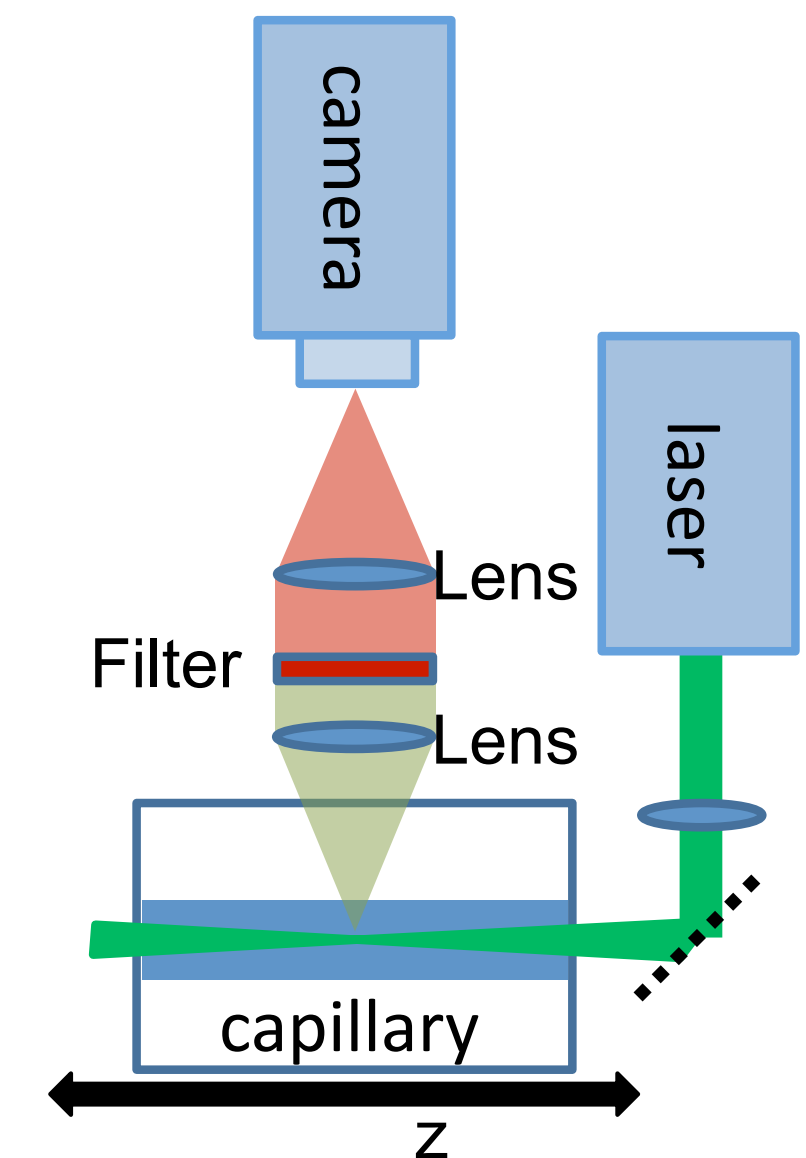
→ T. Weineisen *et al.*, Phys Rev STAB **14**, (2011) 050705



R. Scannell *et al.* Rev. Sci. Instrum. **81**, (2010) 045107

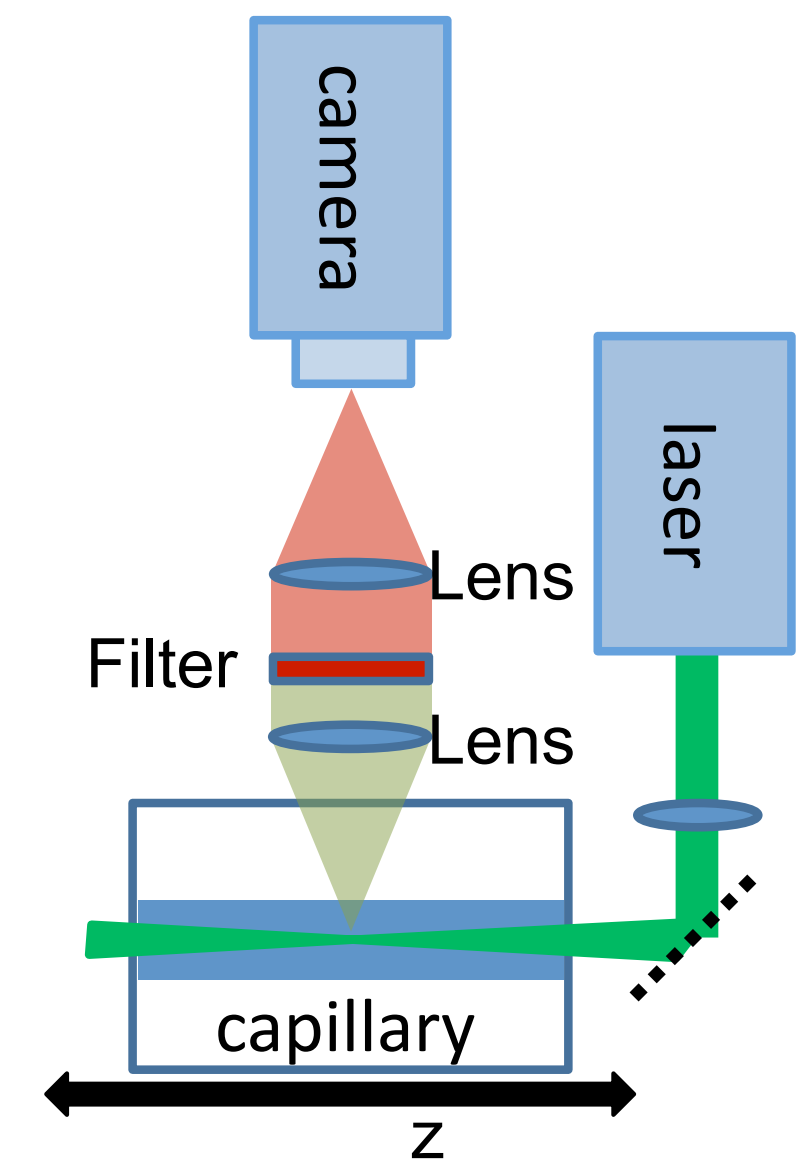
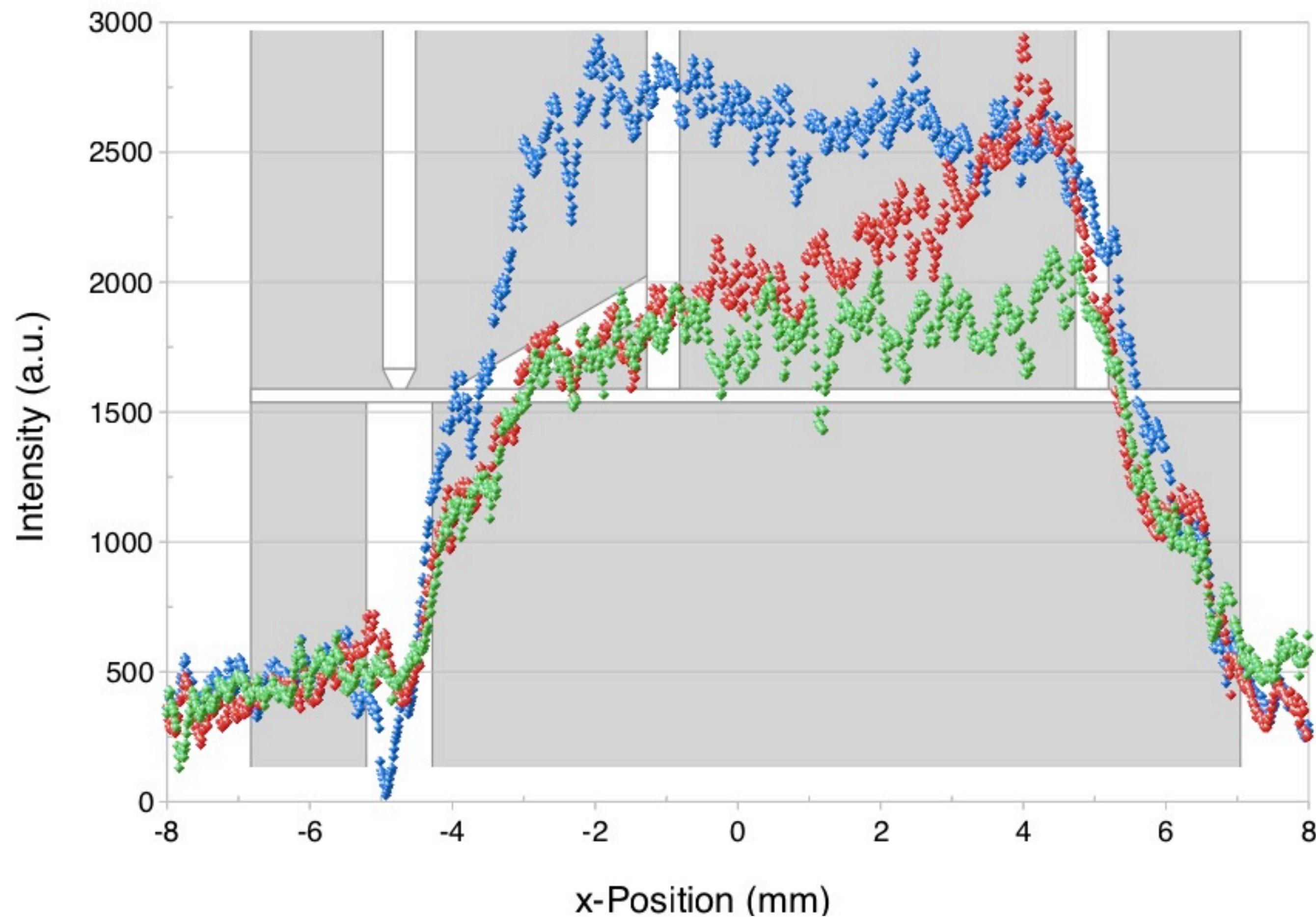


- demonstrated sensitivity: few 10^{18} cm^{-3}
- PW lasers (e.g. BELLA at LBNL) and external injection (e.g. at REGAE) require few 10^{17} cm^{-3}
- Ionization injection experiments: dopant densities down to low 10^{15} cm^{-3}

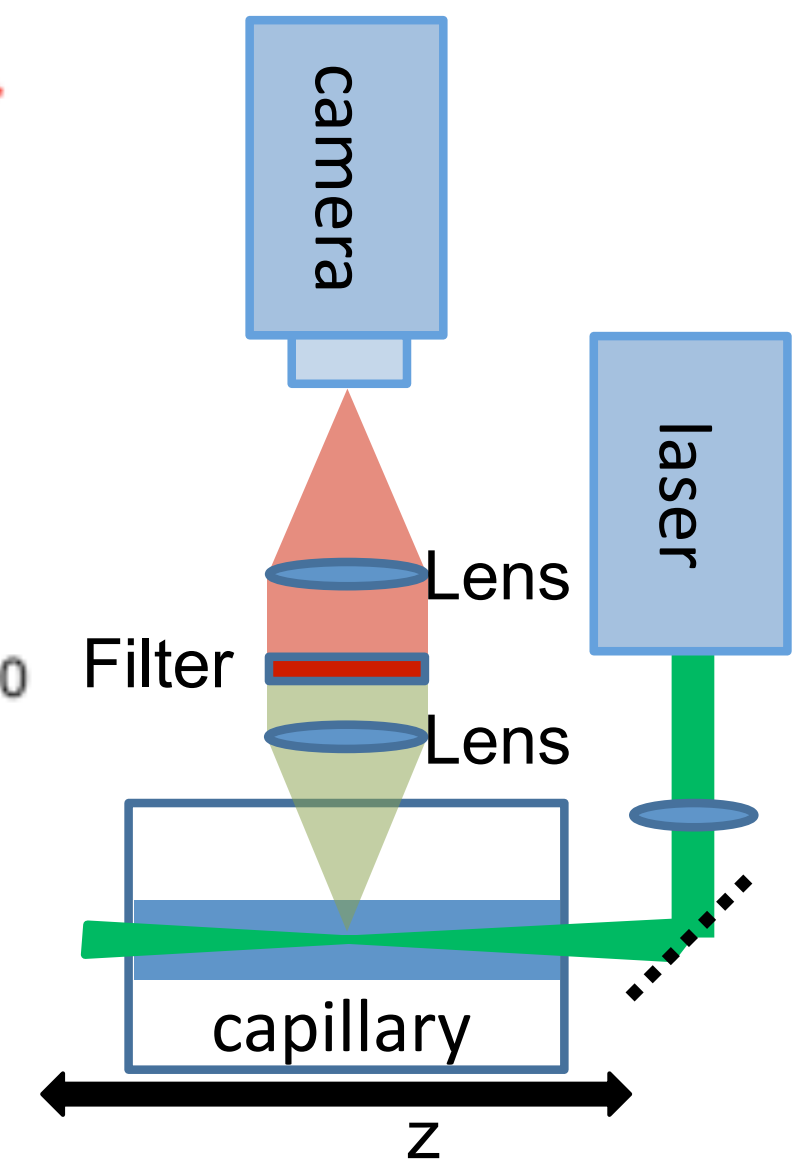
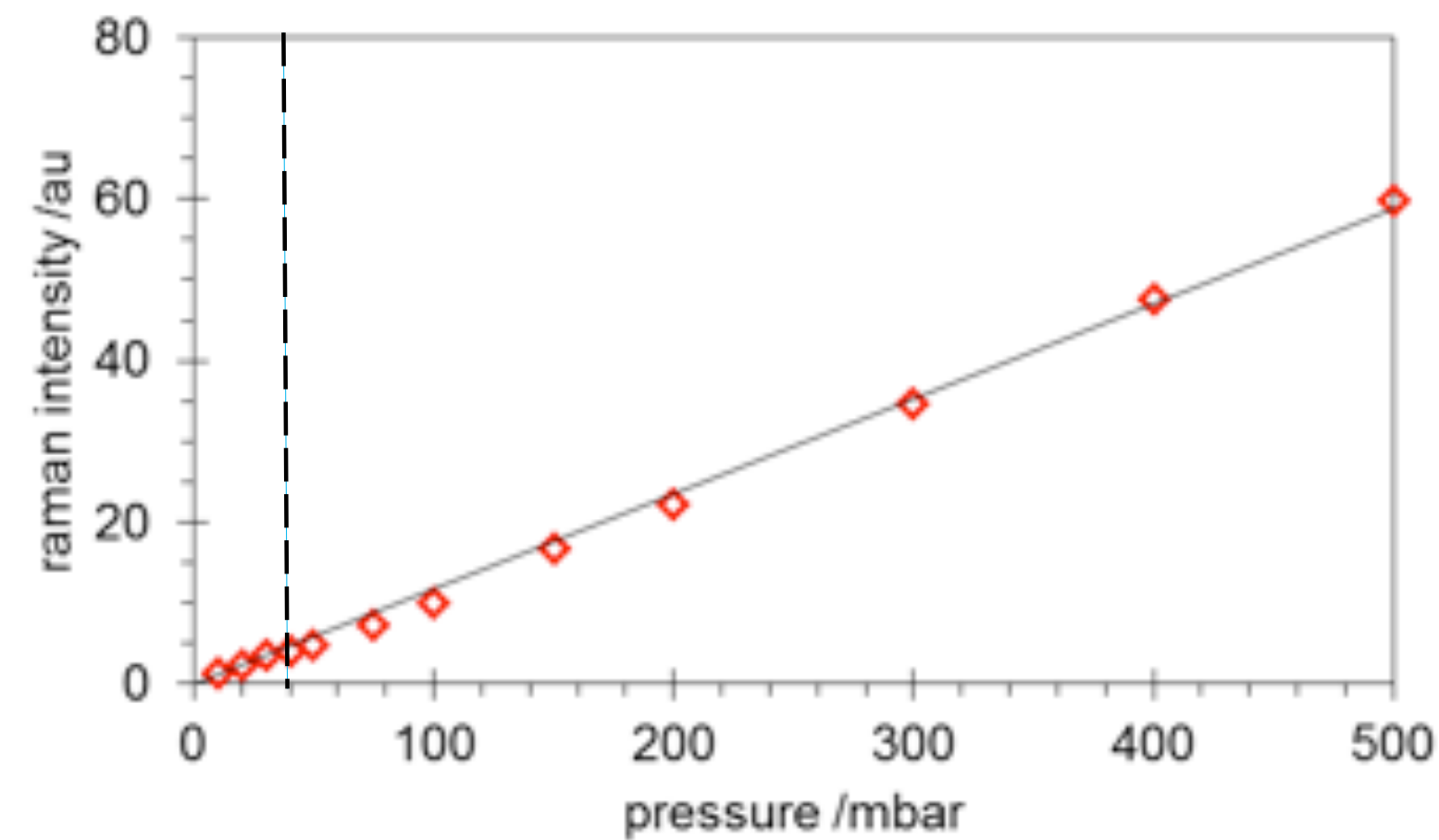
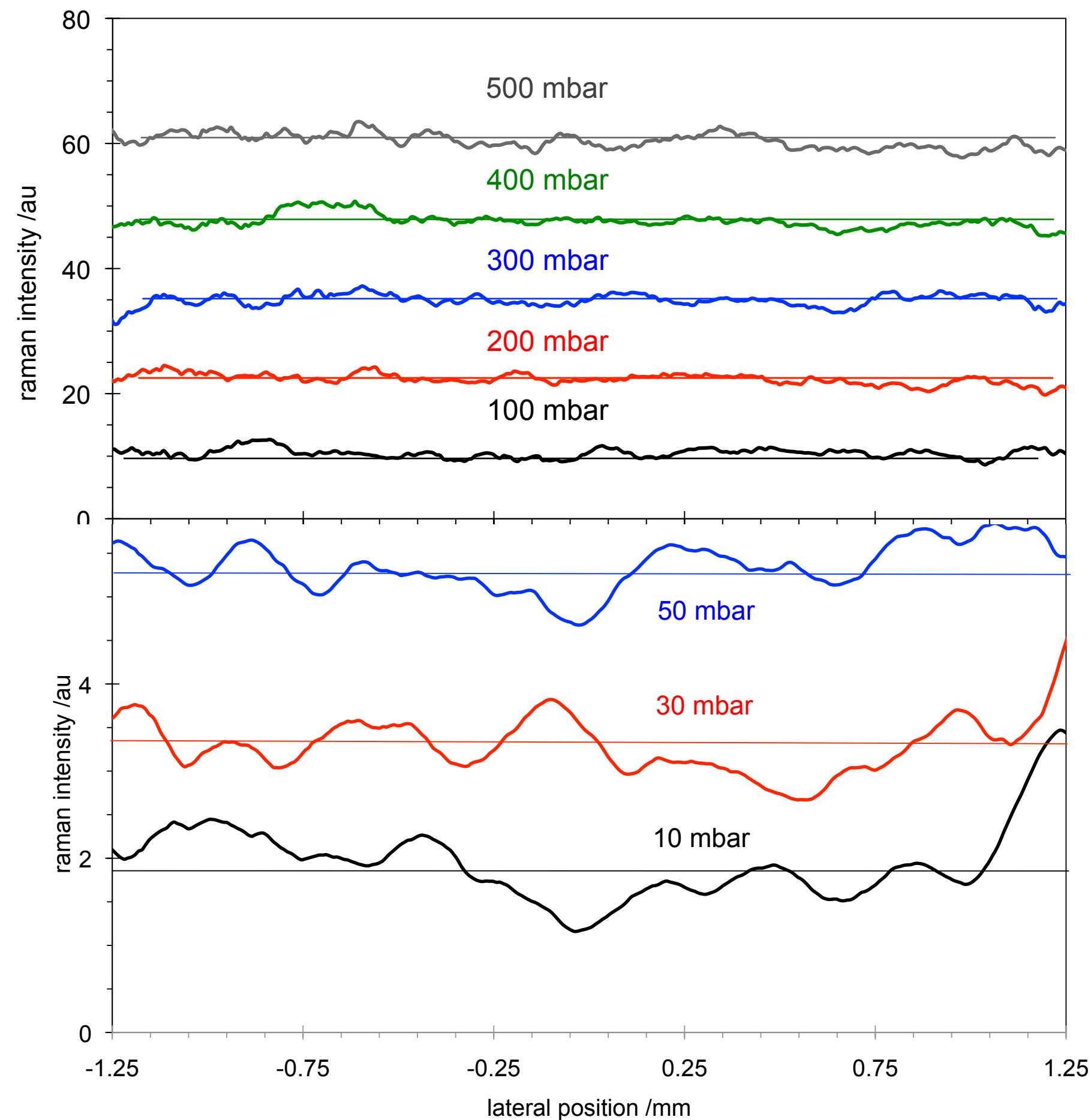


N₂: Shift to first vibrational band = 2329 cm^{-1}
corresponds to 75.2nm (for 532nm excitation)
But: Cross section smaller by 3 orders

Sensitive diagnostic important for profile characterization



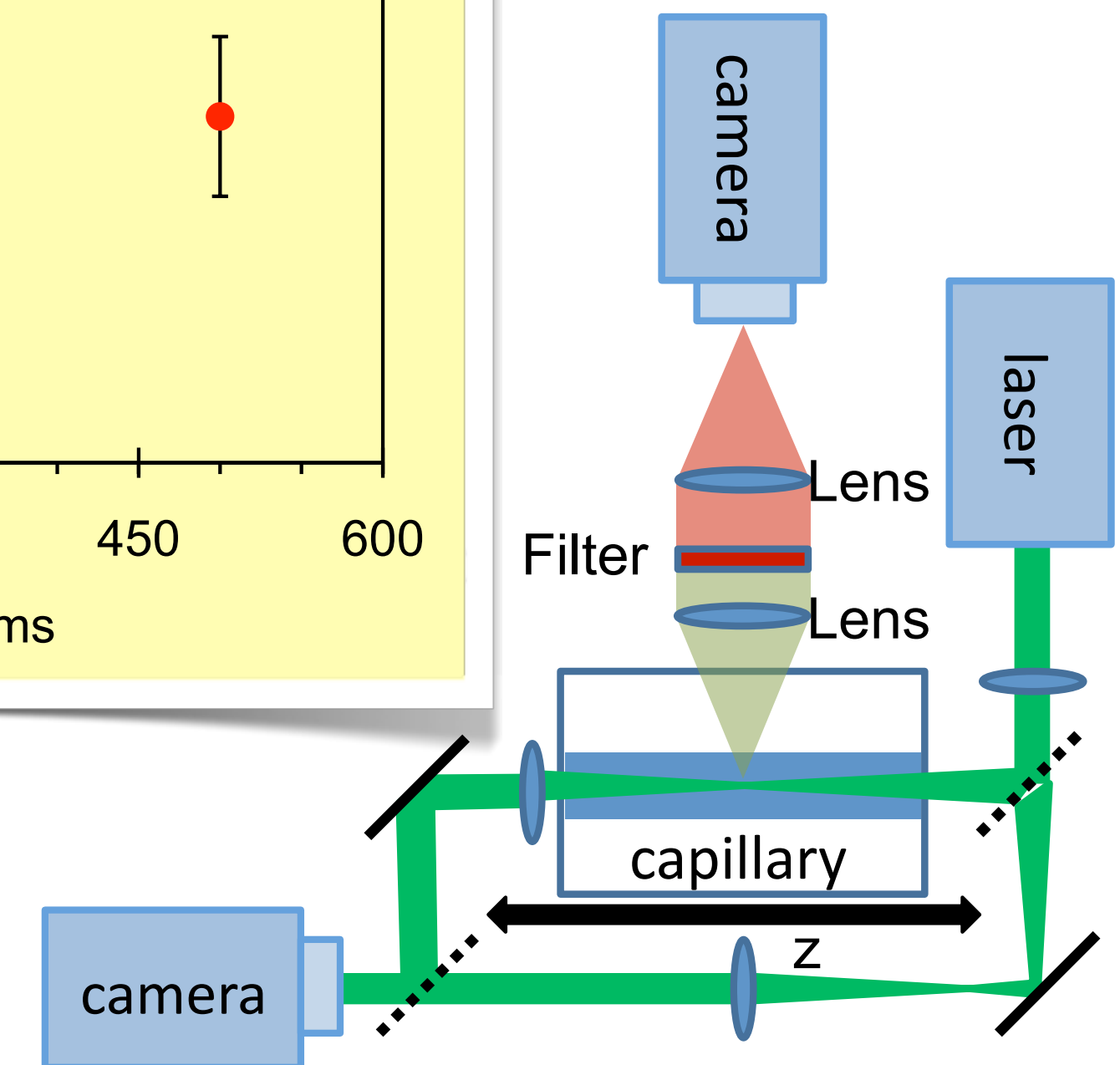
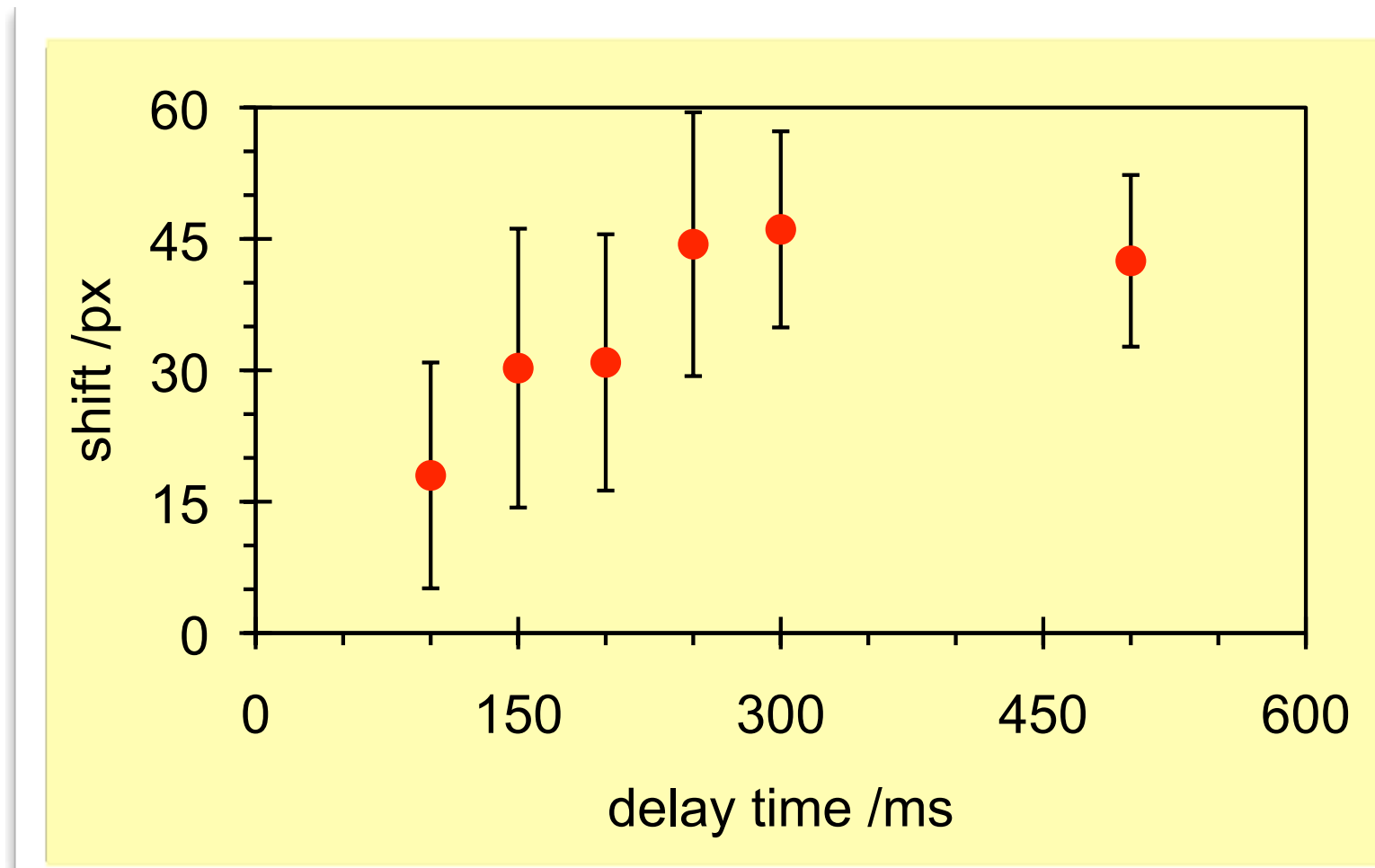
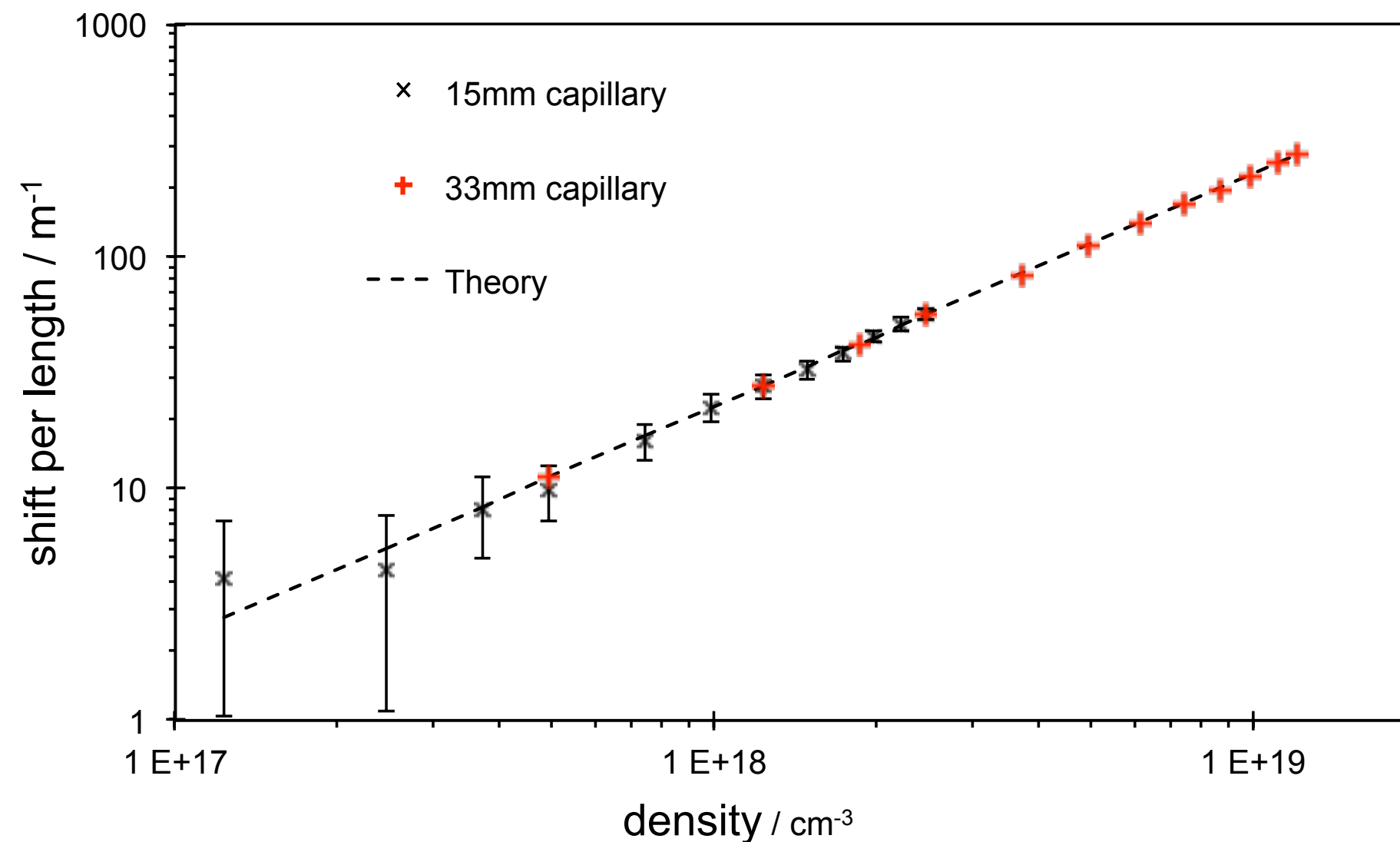
Sensitive diagnostic important for profile characterization



Sensitive diagnostic important for profile characterization

L. F. Schaper *et al.*, in preparation

New technique: Raman scattering combined with longitudinal interferometry



- profile determination by Raman scattering in polished capillaries
- integrated density under profile determined by interferometry

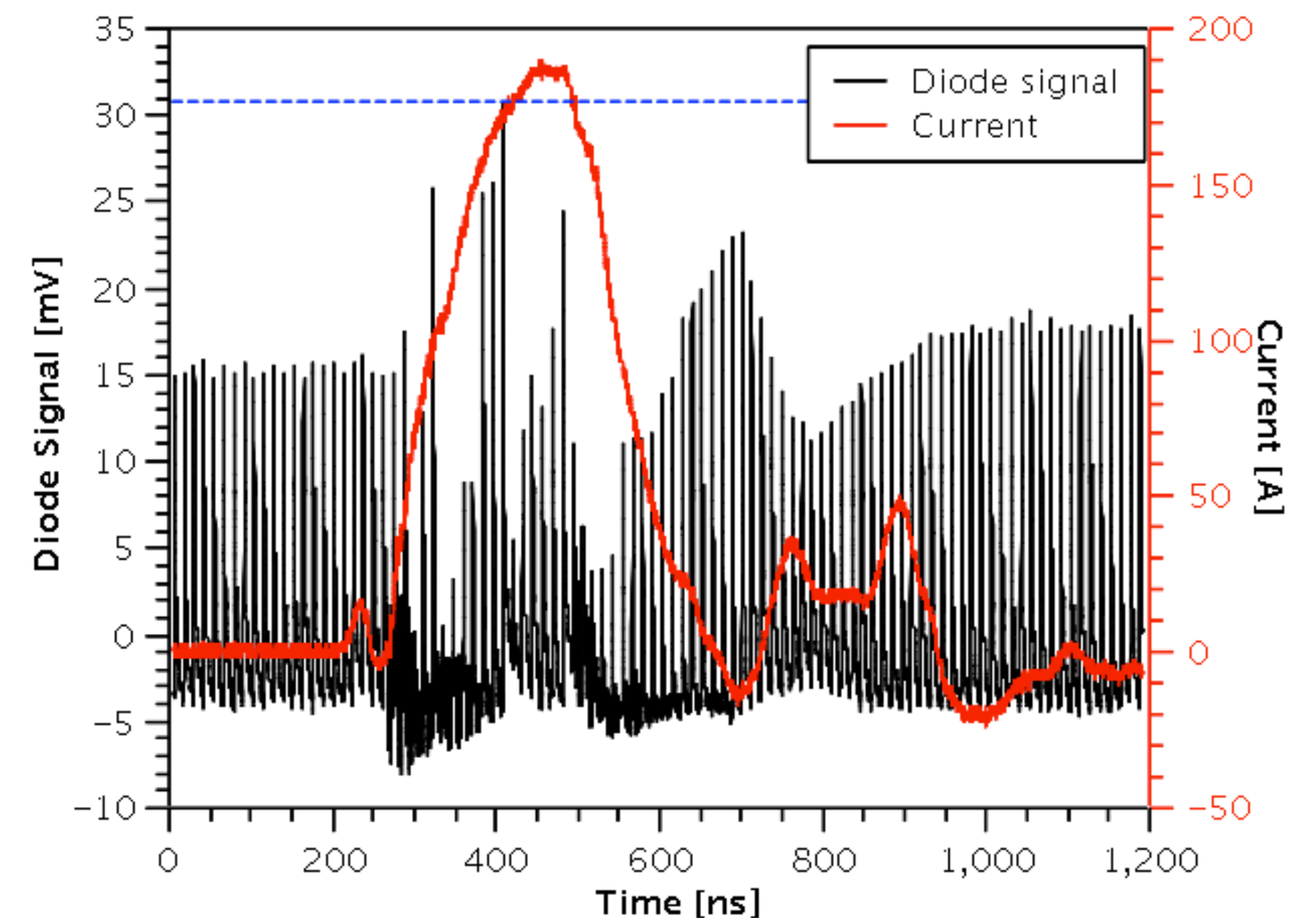
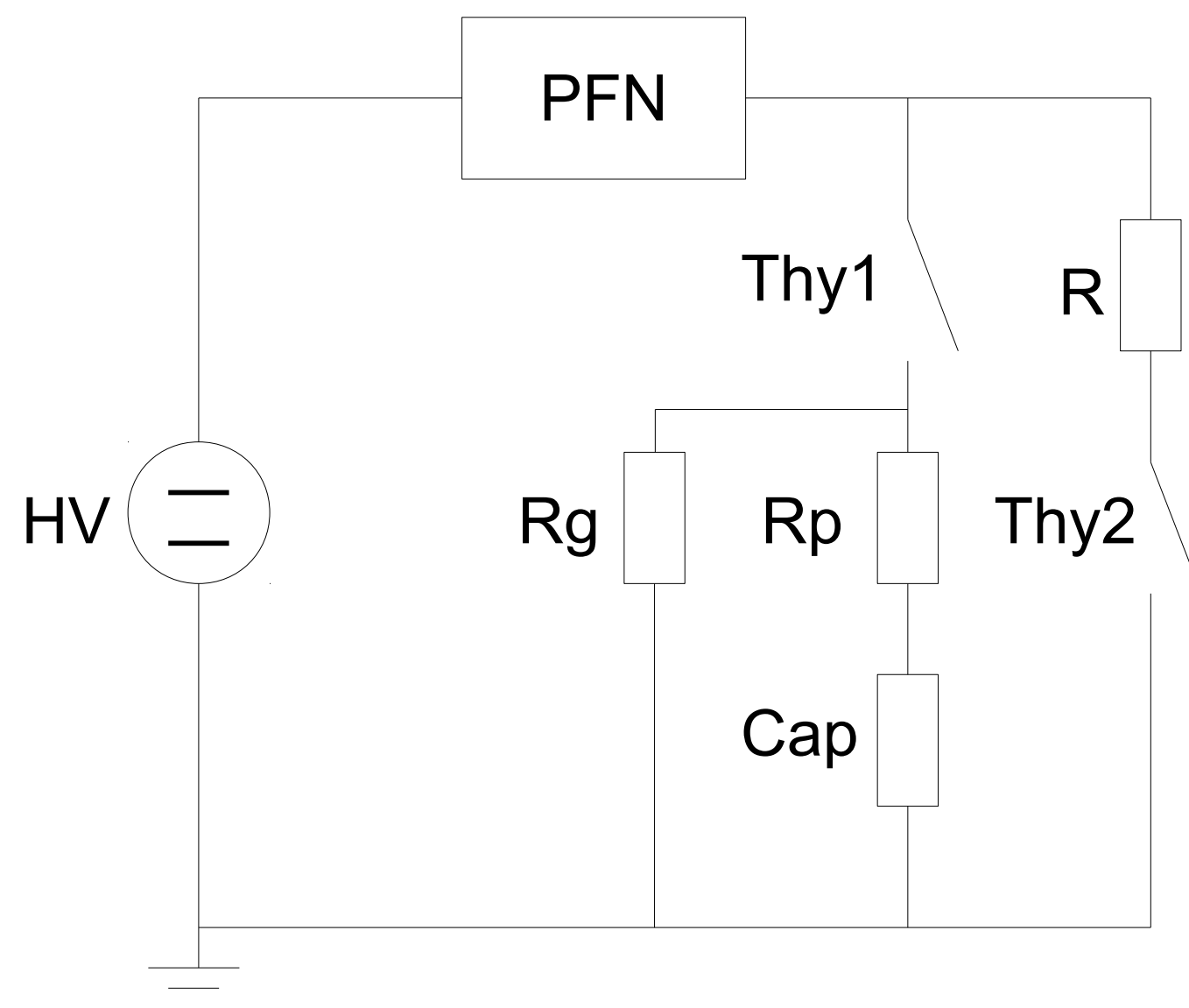
}

→ reconstruction of profile with high accuracy
(currently being done)

Transverse density shaping

Technique: Laser guiding by transverse plasma channel, ignited through electric discharge

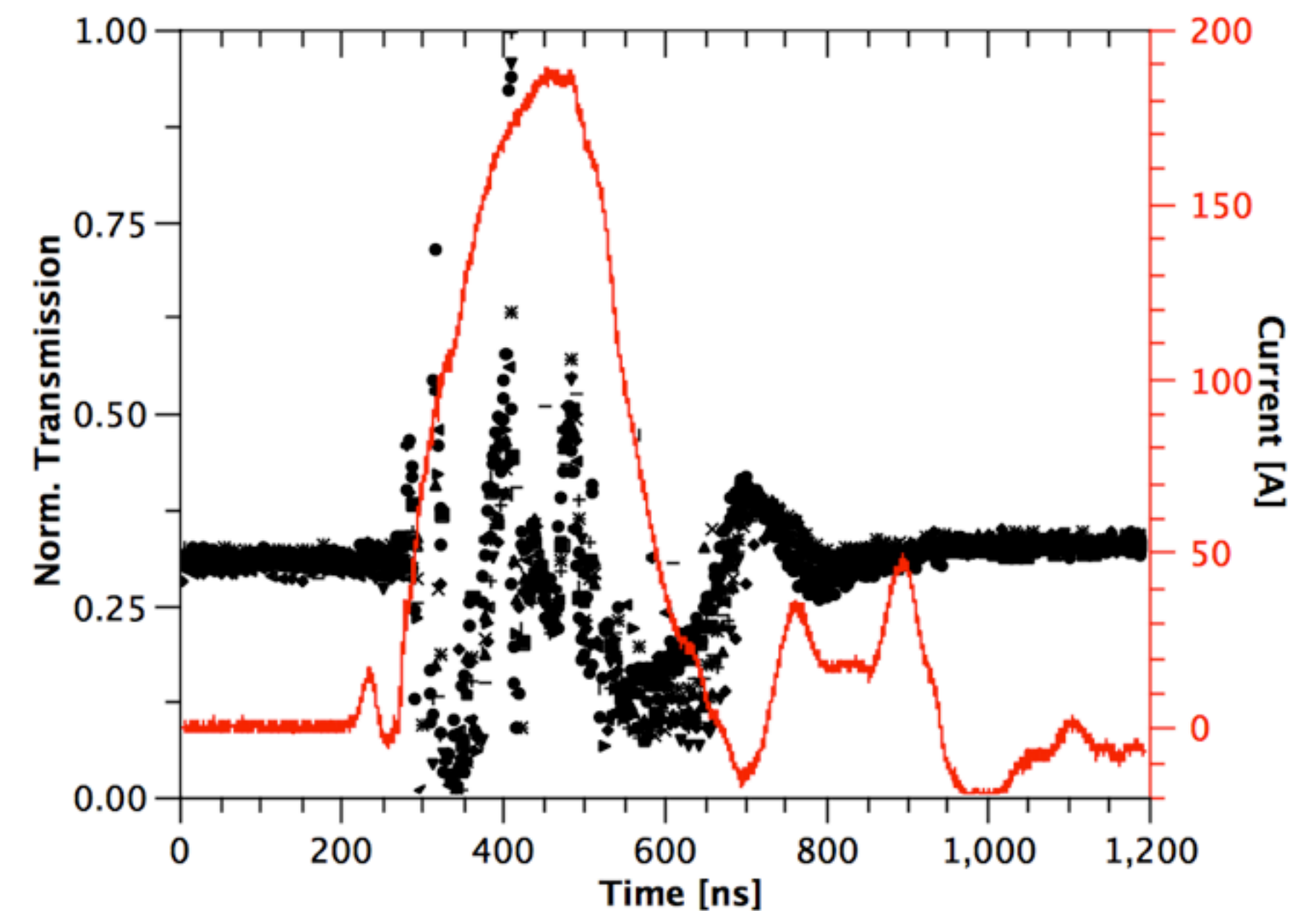
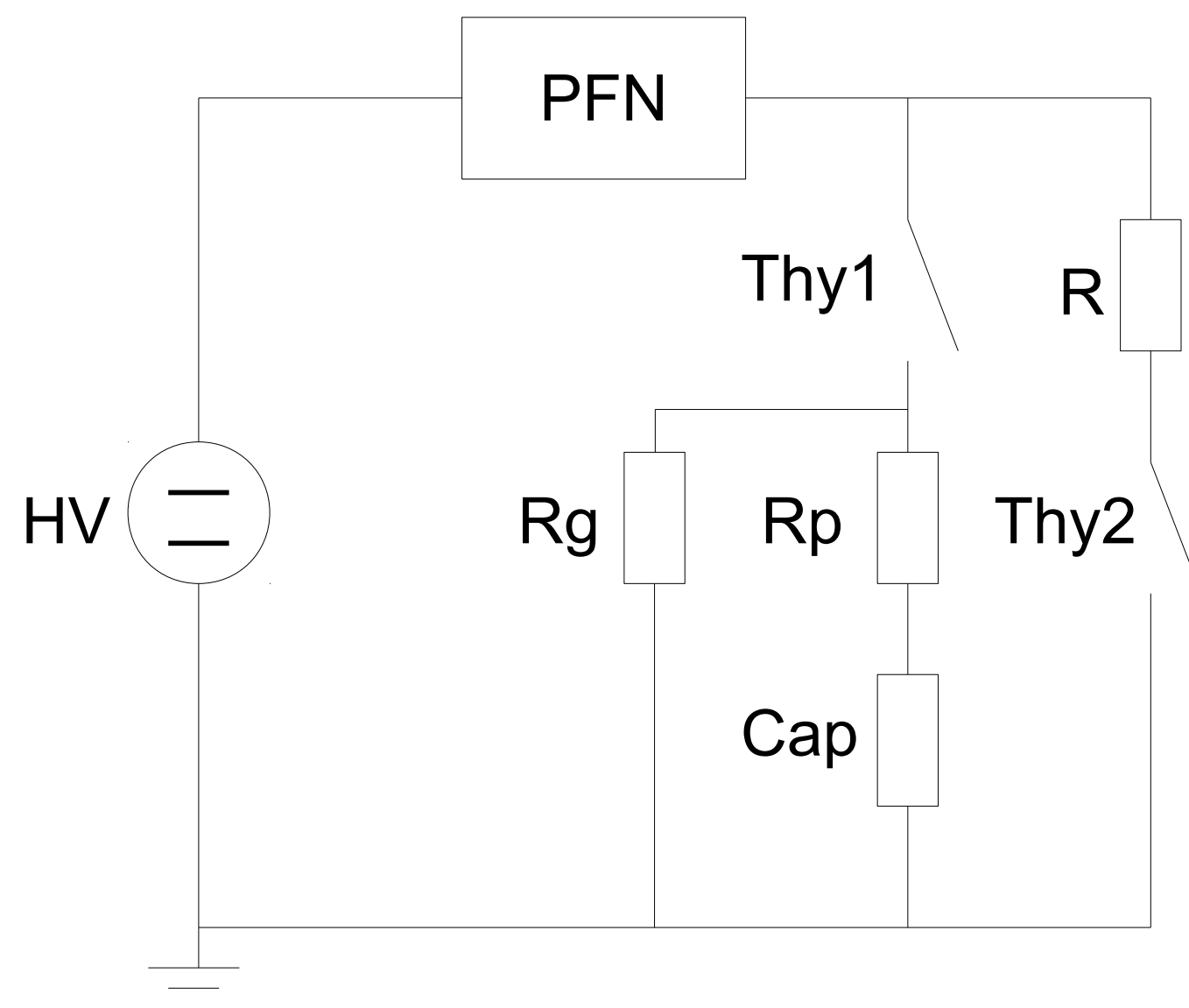
- PFN with adjustable pulse duration and either peak current or di/dt
- Max voltage: 40kV max current: 1.5kA (tested so far) max pulse duration: 400ns
- shot to shot RMS jitter @ 15kV < 5ns



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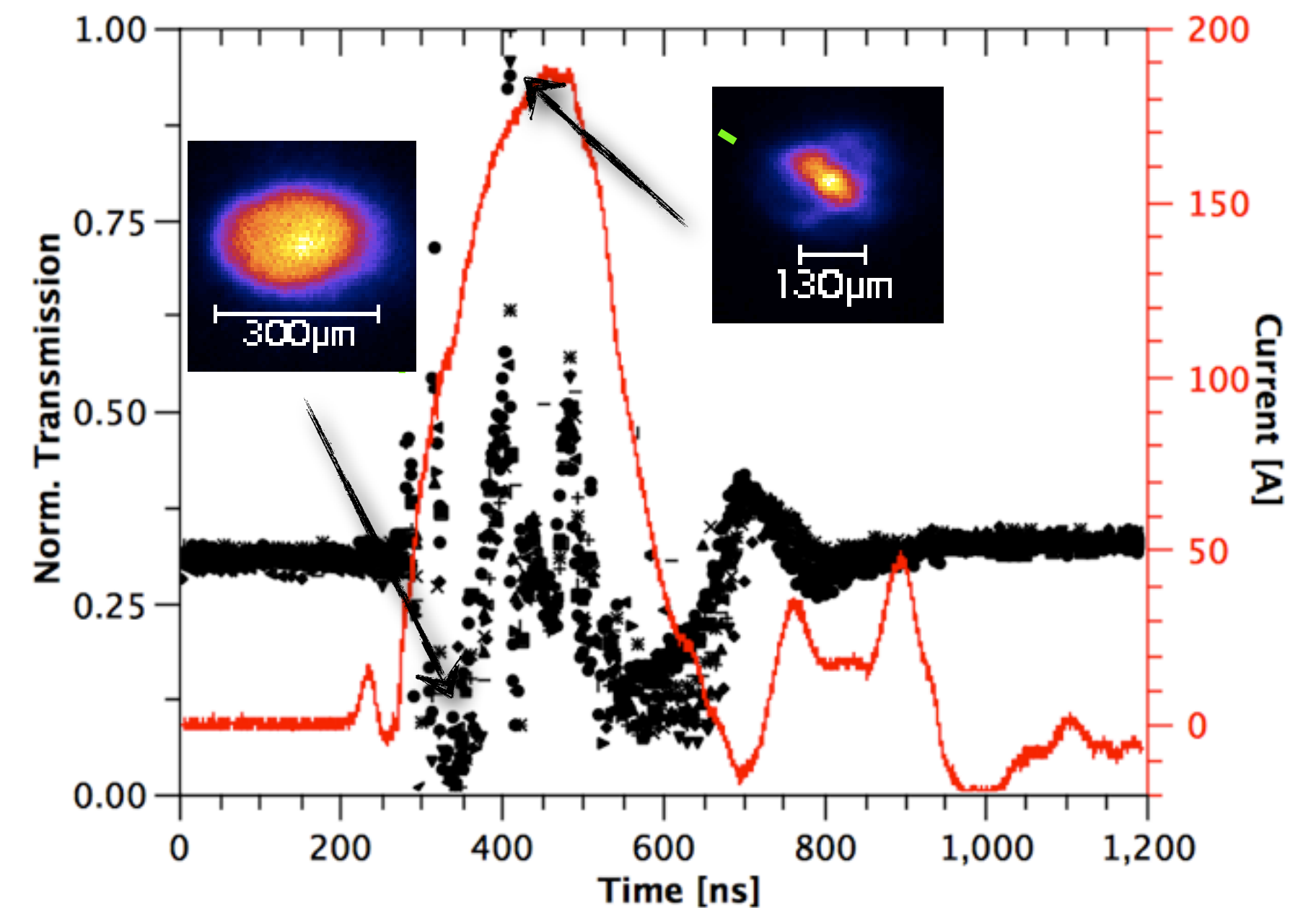
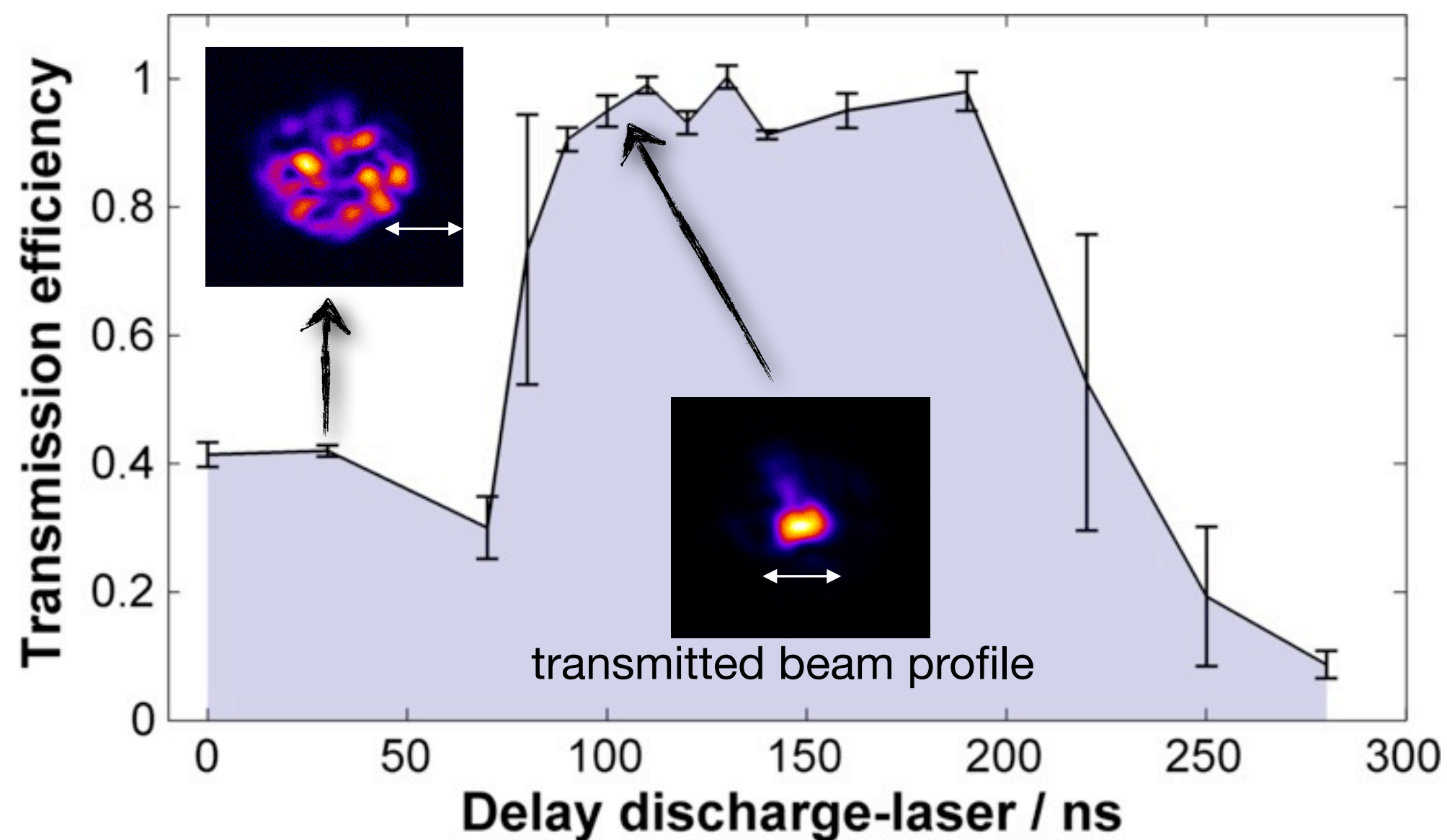


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guiding 15 mm long capillary, laser < 1 mm Rayleigh length



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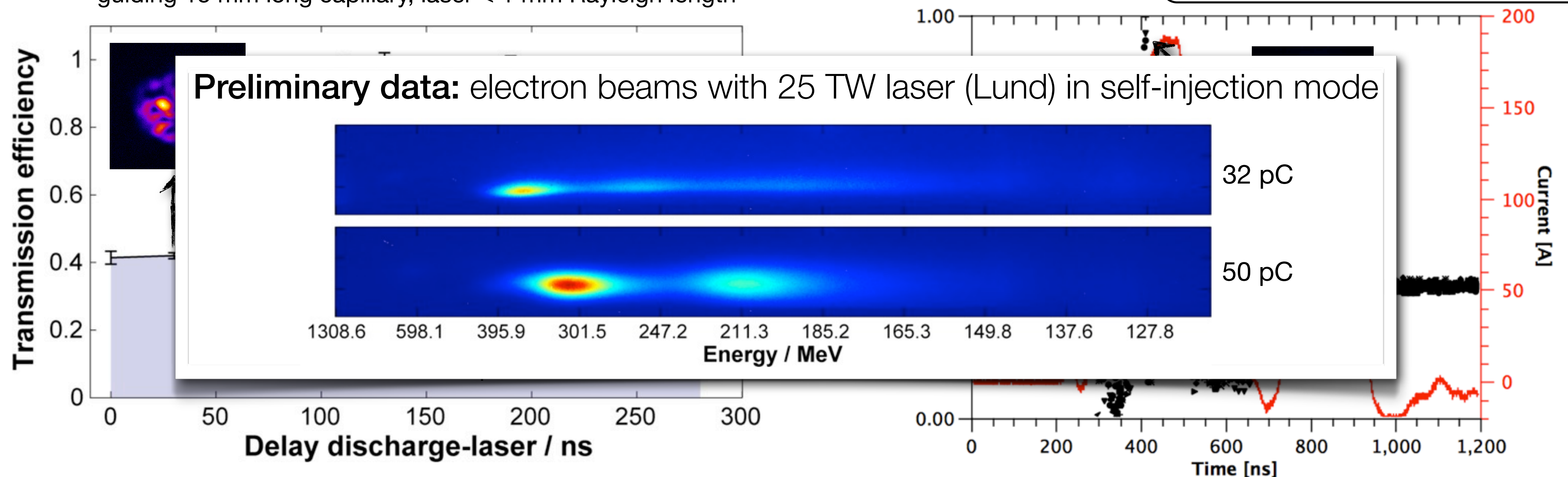
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M. Burza, M. Hansson,
O. Lundh, L. Senje,
C.-G. Wahlstrom



LUND UNIVERSITY

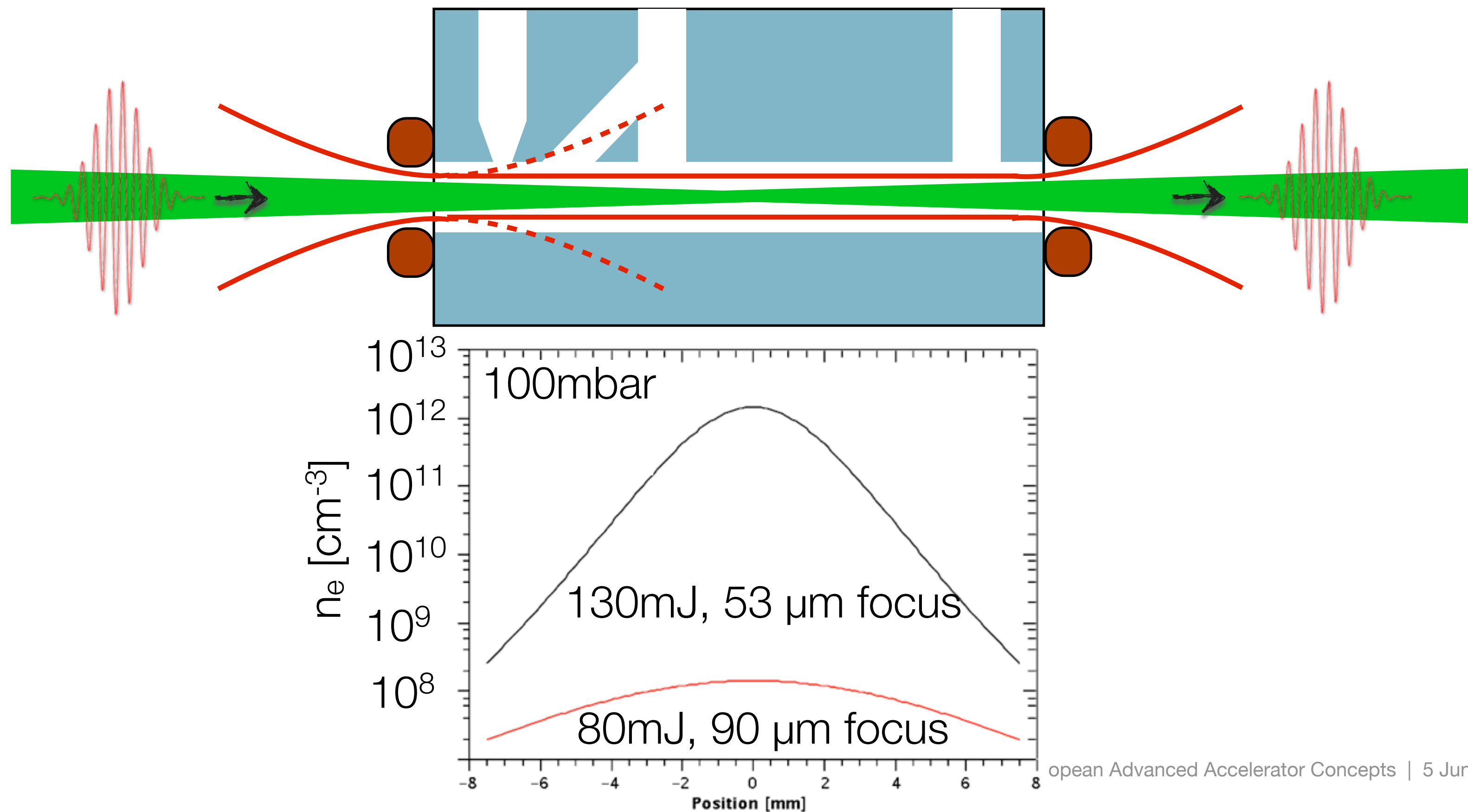
guiding 15 mm long capillary, laser < 1 mm Rayleigh length



Discharge seeding

Technique: Adding a pulsed laser to partially pre-ionize target via multiphoton-ionization

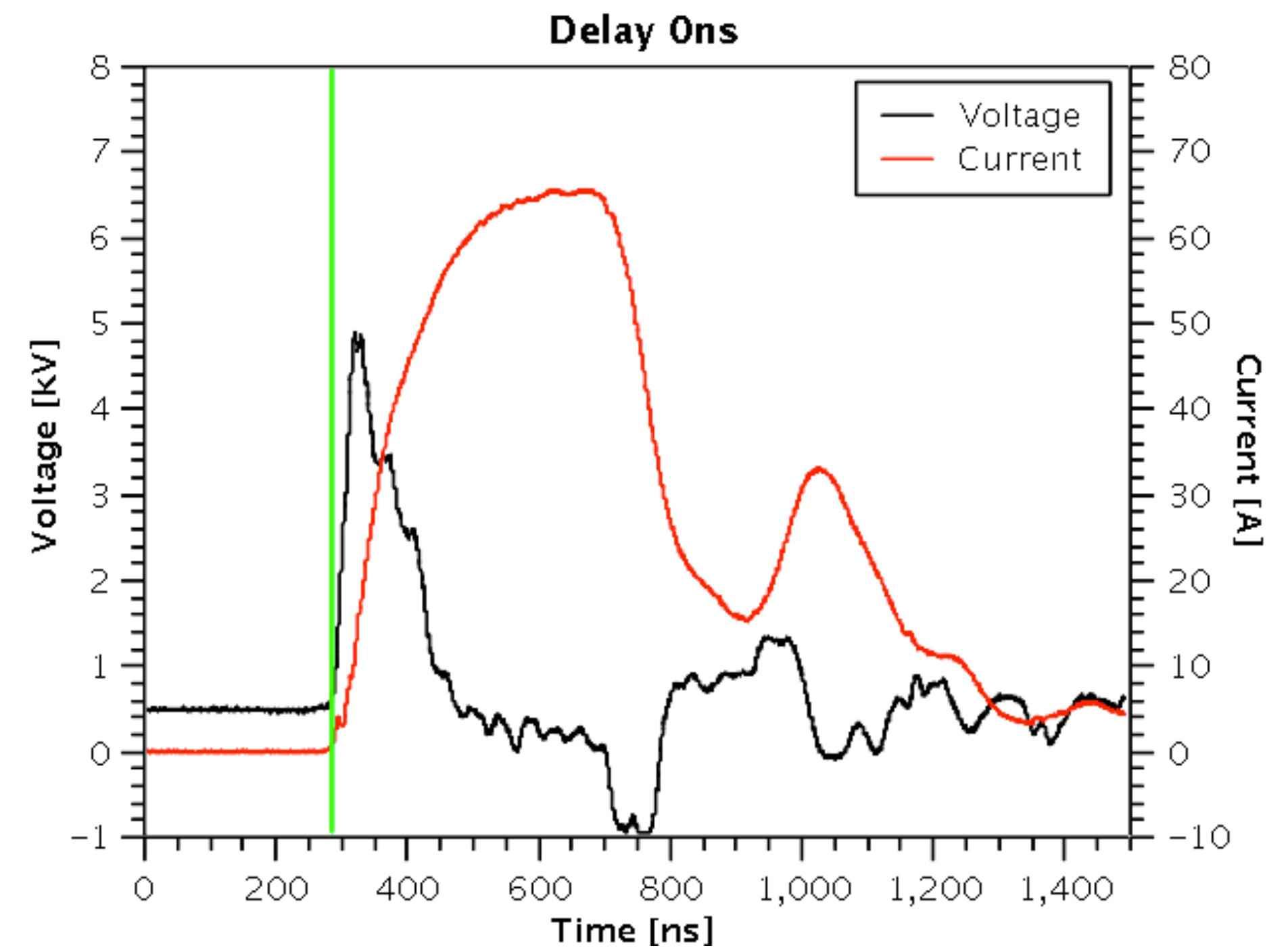
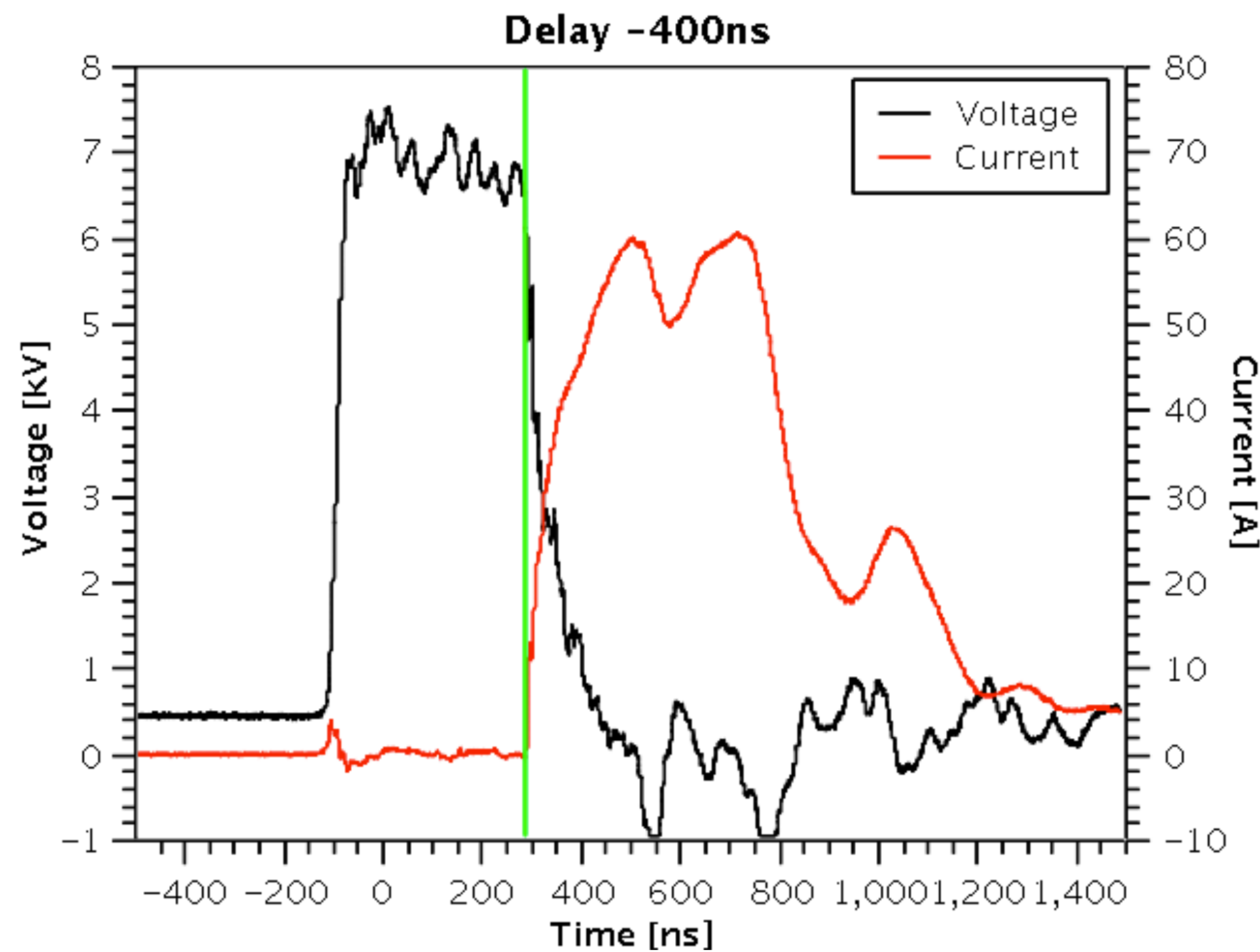
- Reduction of discharge jitter to level of thyatron switching time (about 1ns)
- Result: lower voltages needed, allows for long targets



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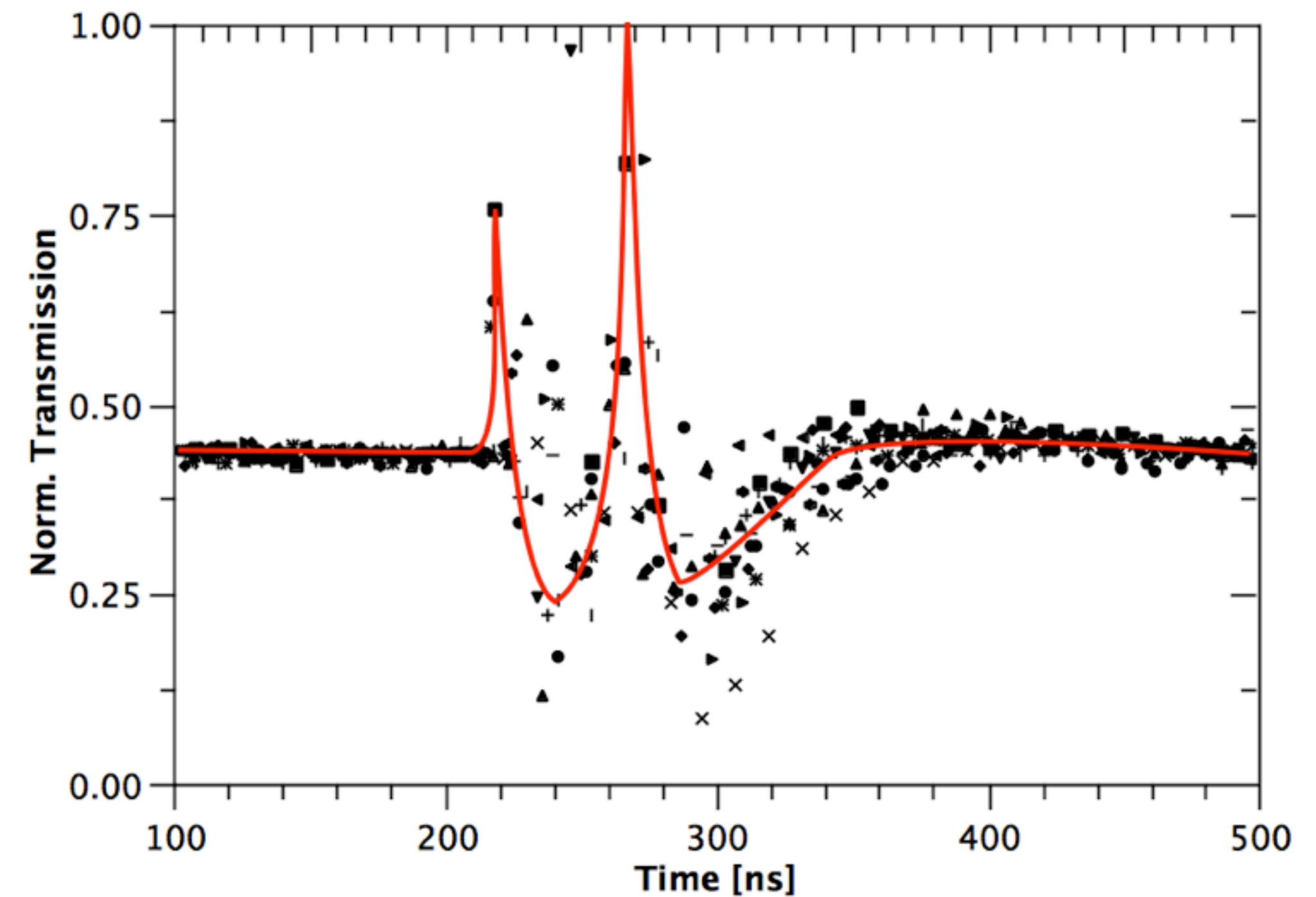
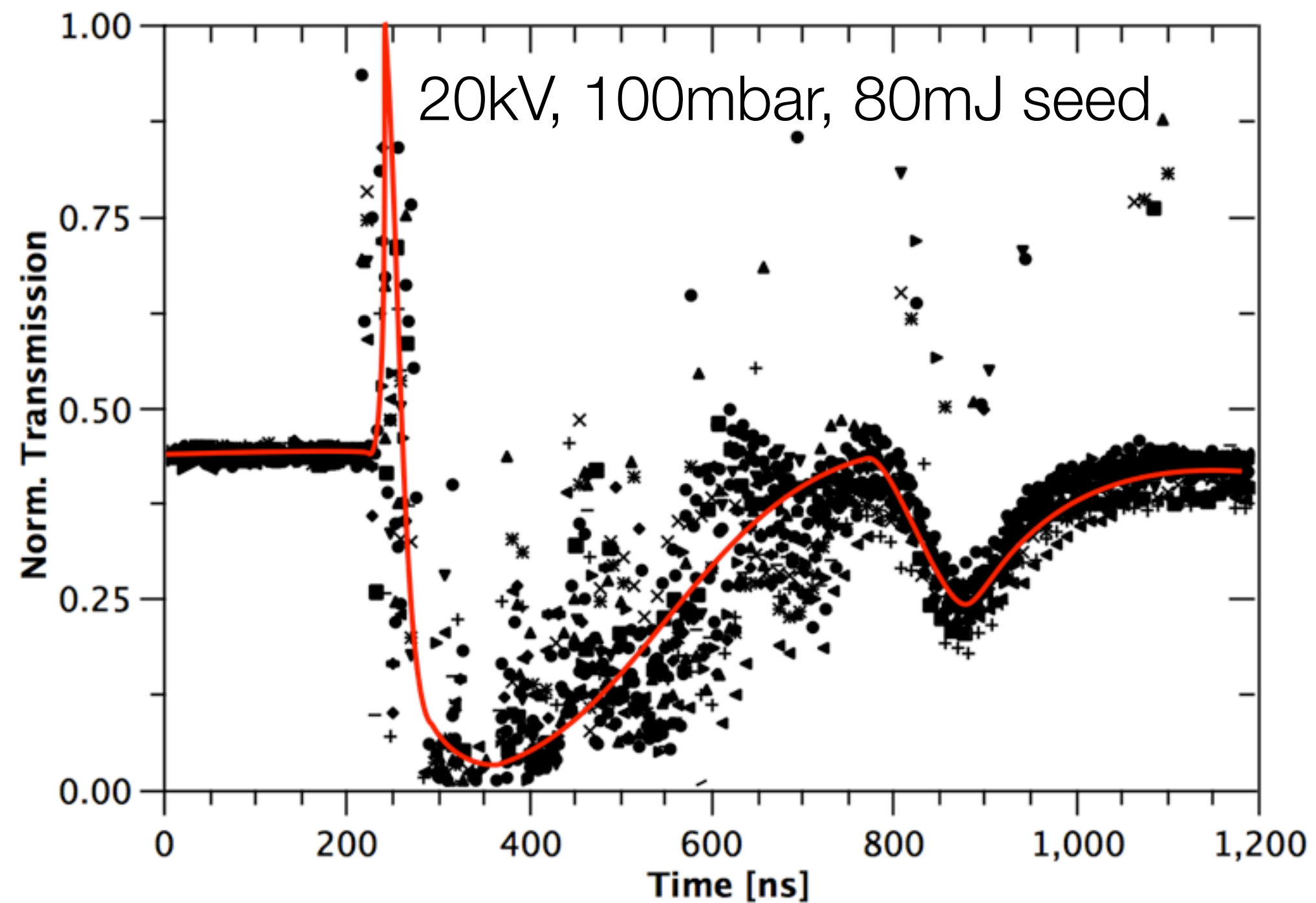
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Summary

> Longitudinal density tailoring

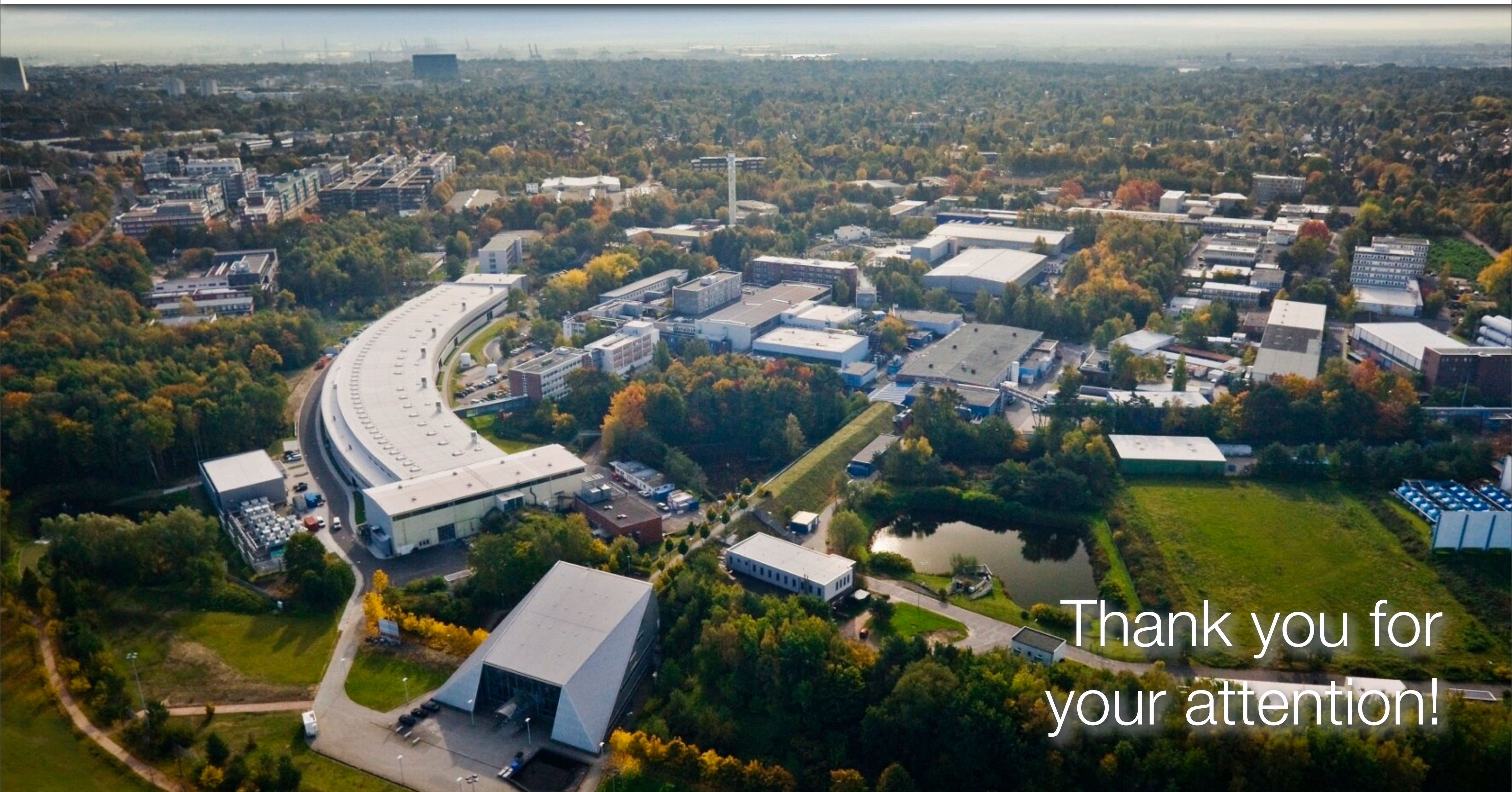
- > Relative density profile measurement down to 10^{17} cm^{-3}
- > Absolute density calibration for fringe shifts $< 5 \times 10^{-3} \text{ mm}^{-1}$
- > results from simulations and measurements agree

> Transverse density shaping

- > PFN allows flexible discharge parameters
- > low discharge-on jitter in typical capillary length at typical voltages of about 20kV
- > High transmission through capillaries with length \gg Rayleigh length of the laser

> Discharge seeding

- > increased stability and decrease discharge time lag
- > stable operation at lower voltages, longer capillaries possible
- > BUT: Not guiding (so far)



Thank you for
your attention!